

Radiation tolerance study

using test-structure diodes
from 8-inch silicon sensors
for CMS HGCAL

Jan Kieseler,

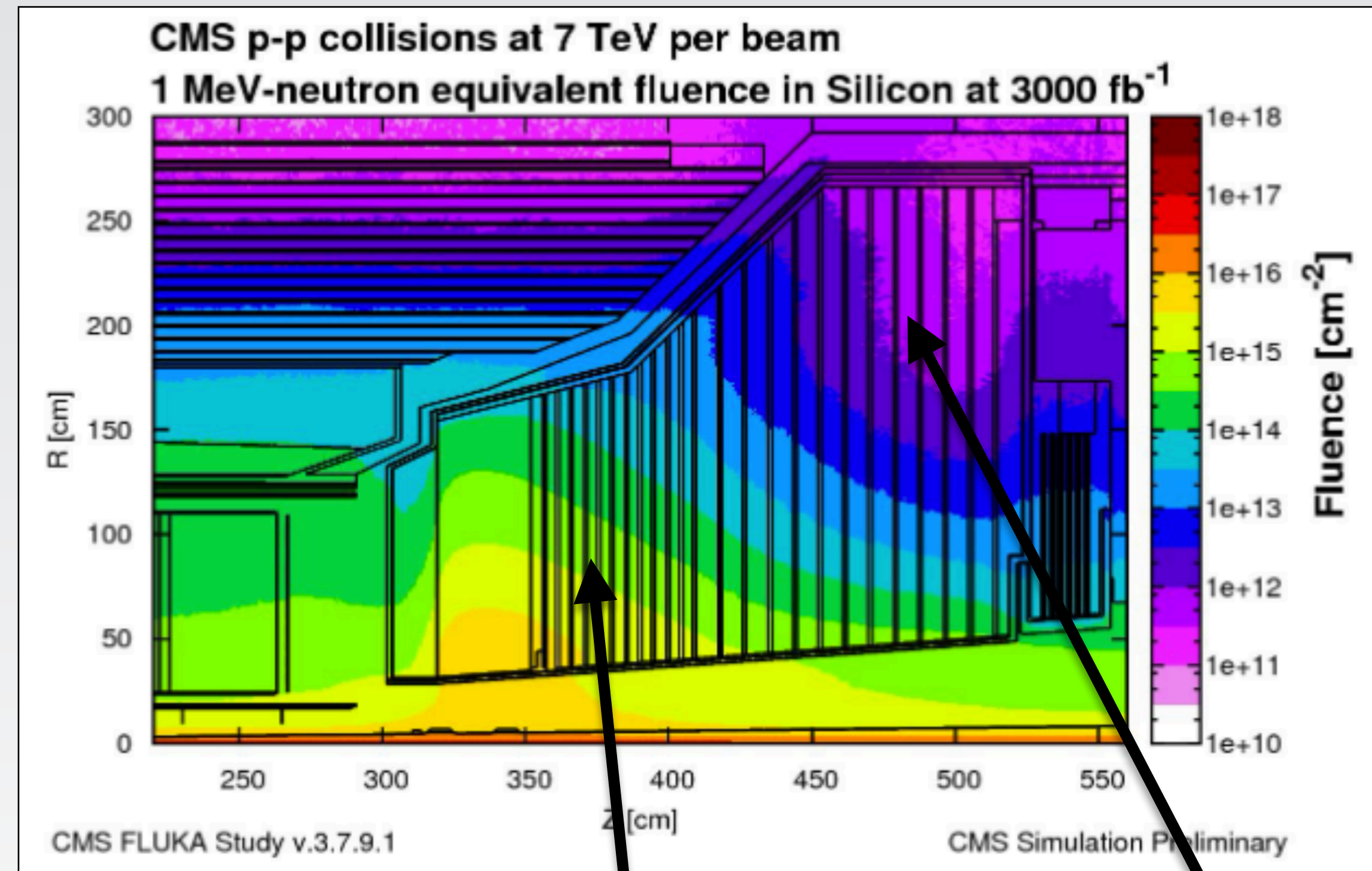
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with support from the CERN SSD group

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Introduction and Outline

- High fluences up to 10^{16} neq/cm²
- Two different sensor types, different optimal annealing scenarios
- Large area to cover with Si sensors: **new production line for 8" wafers** [Full sensor results in [Oliwia's talk](#)]
- **Annealing behaviour has not been studied**
- Crucial input for operation and warming up scenarios



This talk: annealing behaviour of silicon bulk material

- Depletion voltage
- Leakage current
- Charge collection efficiency

Silicon sensors
(diodes)

Scintillator+
SiPMs

Studied Samples

- Thickness and material
 - 300µm, 200µm FZ
 - 120µm EPI
- Fluences
 - 6.5e14 to 1e16 neq/cm2
 - Neutron irradiated at JSI

CV/IV

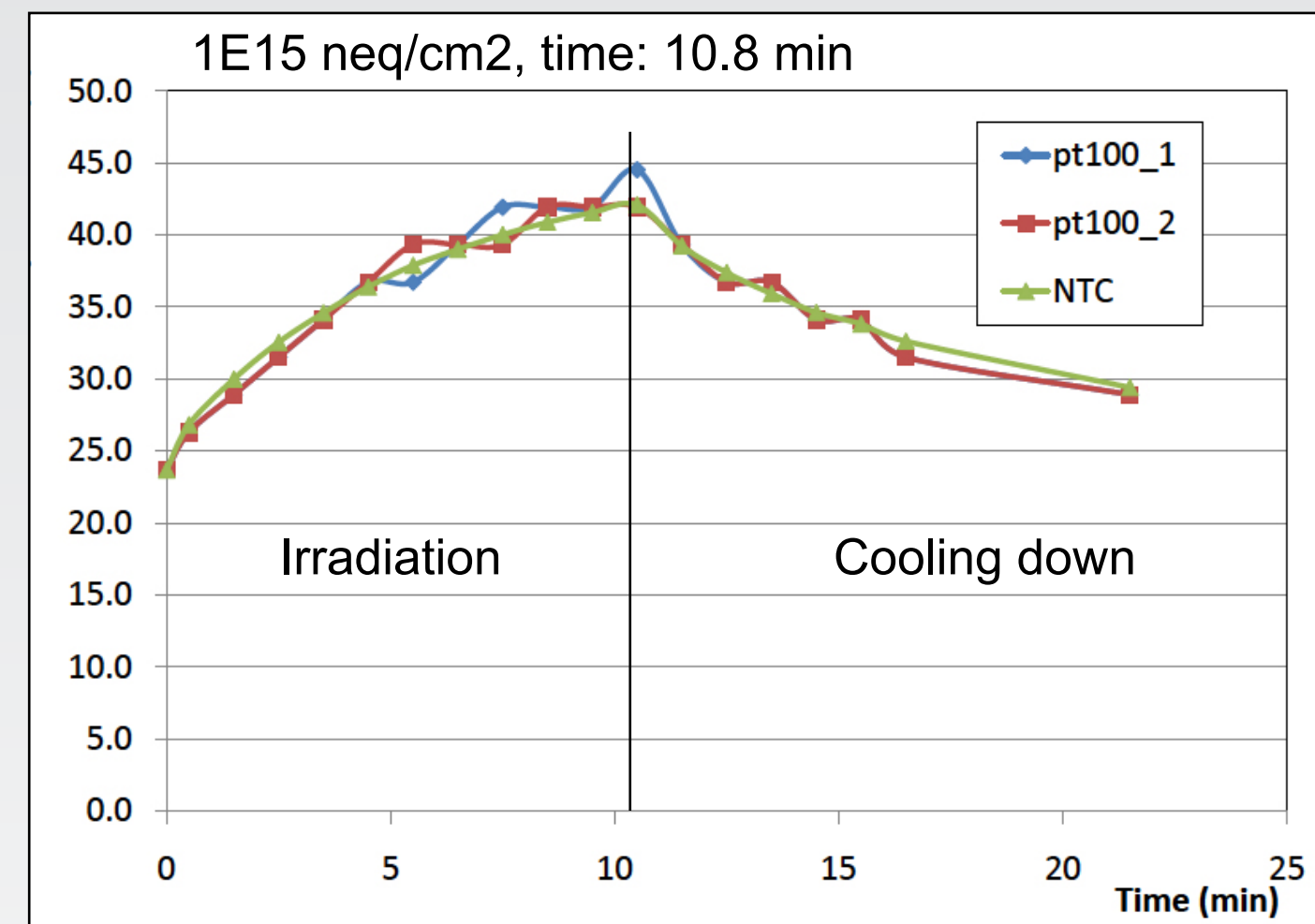
- 16 samples in total
- 9 Annealing points
- ➔ Approx 150 measurements

CCE

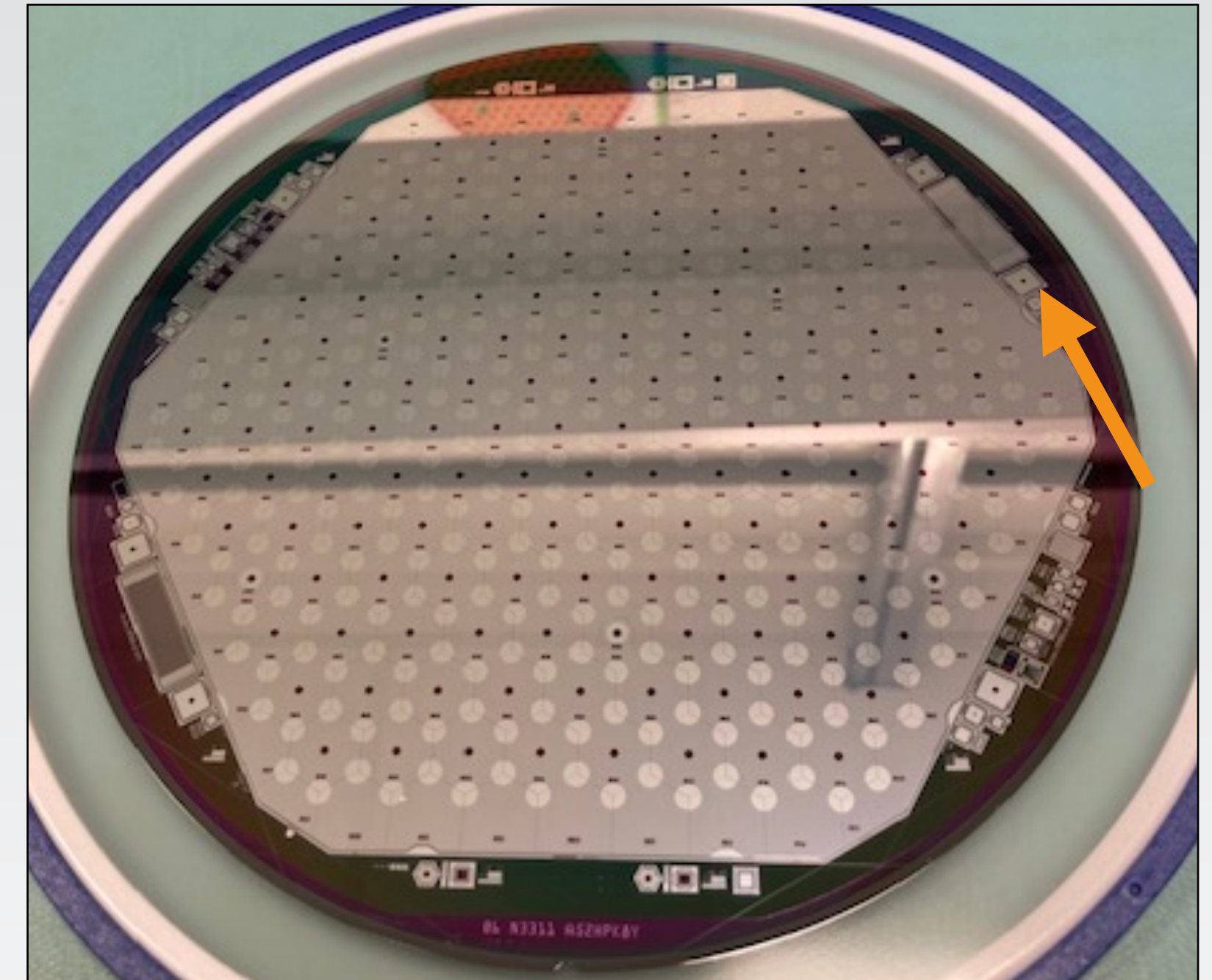
- 12 samples
- 6 Annealing points
- ➔ Approx 70 measurements

Annealing offset correction

- Assume homogenous linear increase in total accumulated fluence during irradiation
- Fold with recorded temperature profile: not expected to exceed +45°C

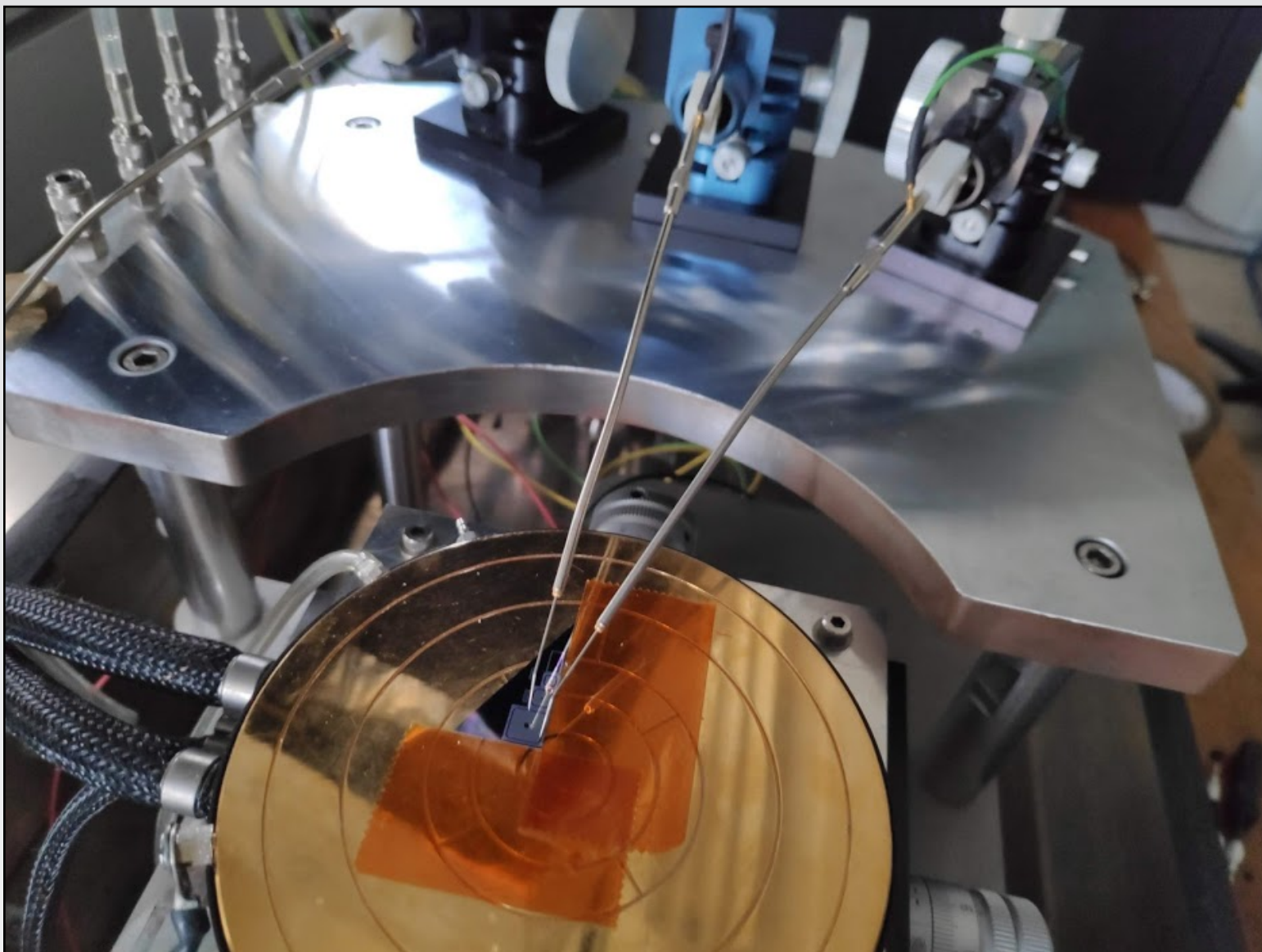


Cindro et al, NIMA

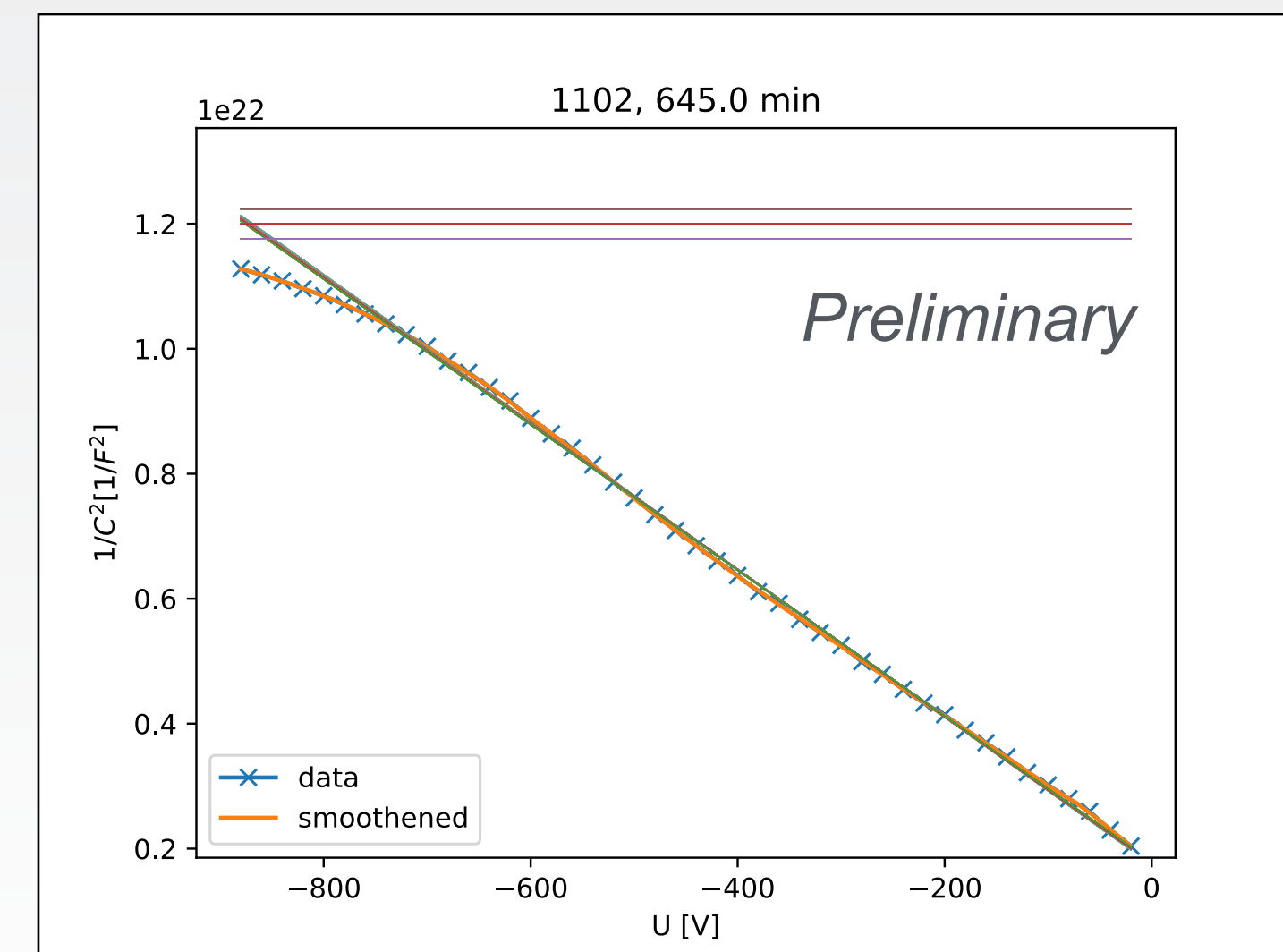
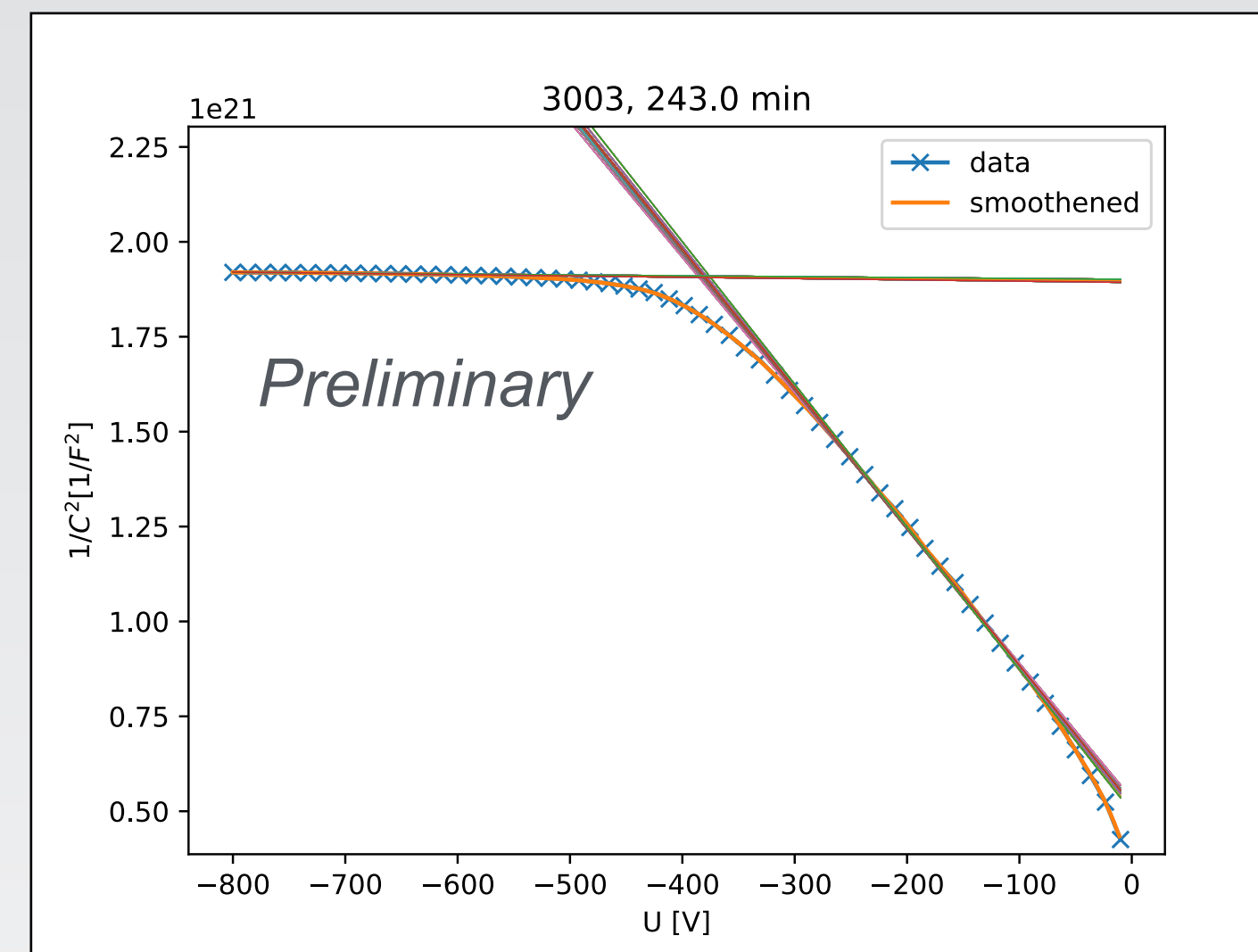


Thick- ness	Flat band volt.	Oxide quality	Proc.	Fluence [neq/cm2]
300	-2V	STD	FZ	6.50E+14
300	-2V	STD	FZ	1.00E+15
300	-2V	STD	FZ	1.50E+15
200	-2V	STD	FZ	1.00E+15
200	-2V	STD	FZ	1.50E+15
200	-2V	STD	FZ	2.50E+15
120	-2V	STD	EPI	1.00E+16
120	-2V	STD	EPI	2.50E+15
120	-2V	STD	EPI	1.50E+15

Capacitance and depletion voltage



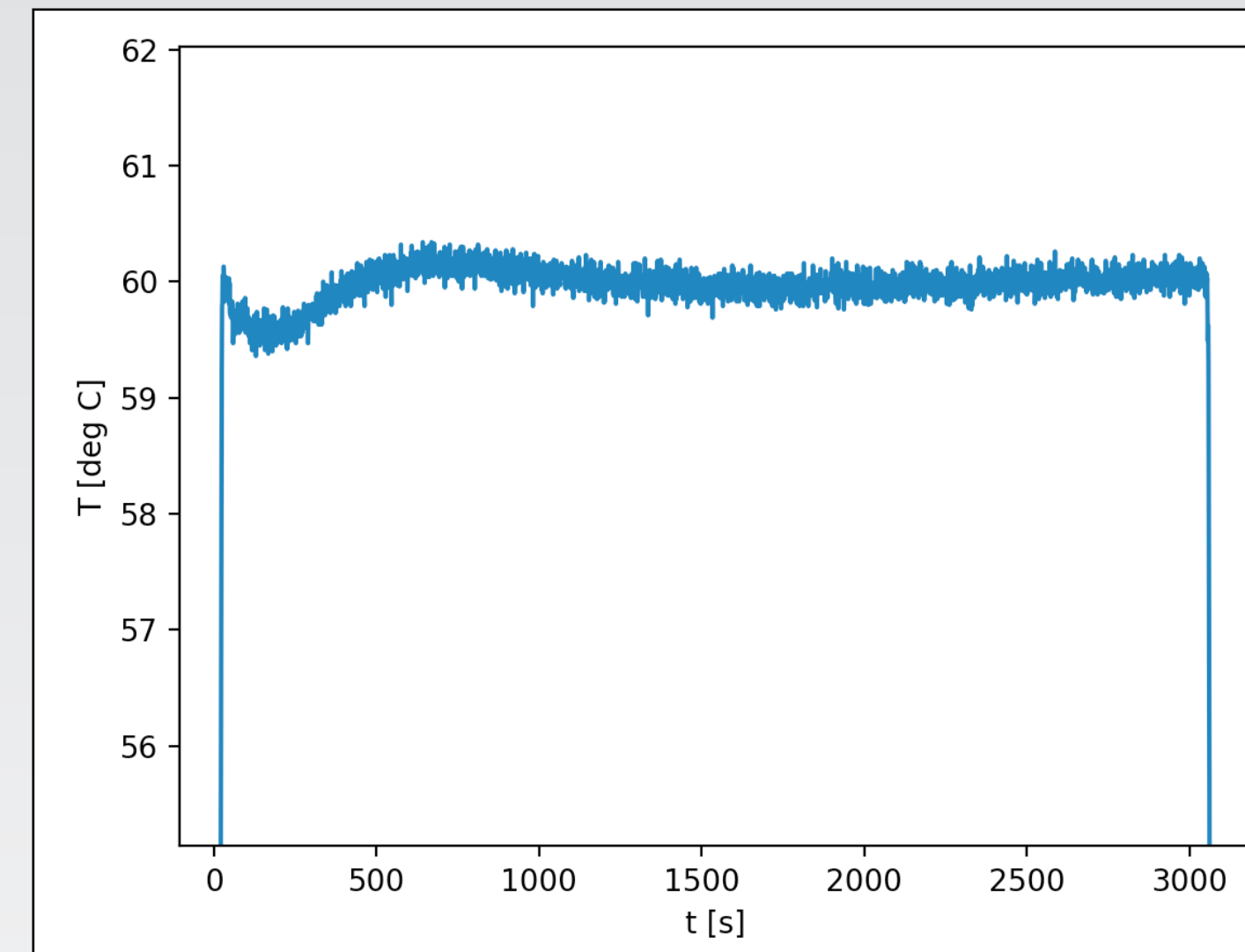
- Measurements performed in the CERN SSD lab
 - 10kHz, 0.5 V
 - Temperature: -20°C
- Fit straight lines
- Choose ranges by hand
 - Assign 10% uncertainty to range choice
- If plateau cannot be reached use expected end capacitance: extrapolation
 - Assign larger uncertainty
- Use as total uncertainty the envelope of all possible intersection points



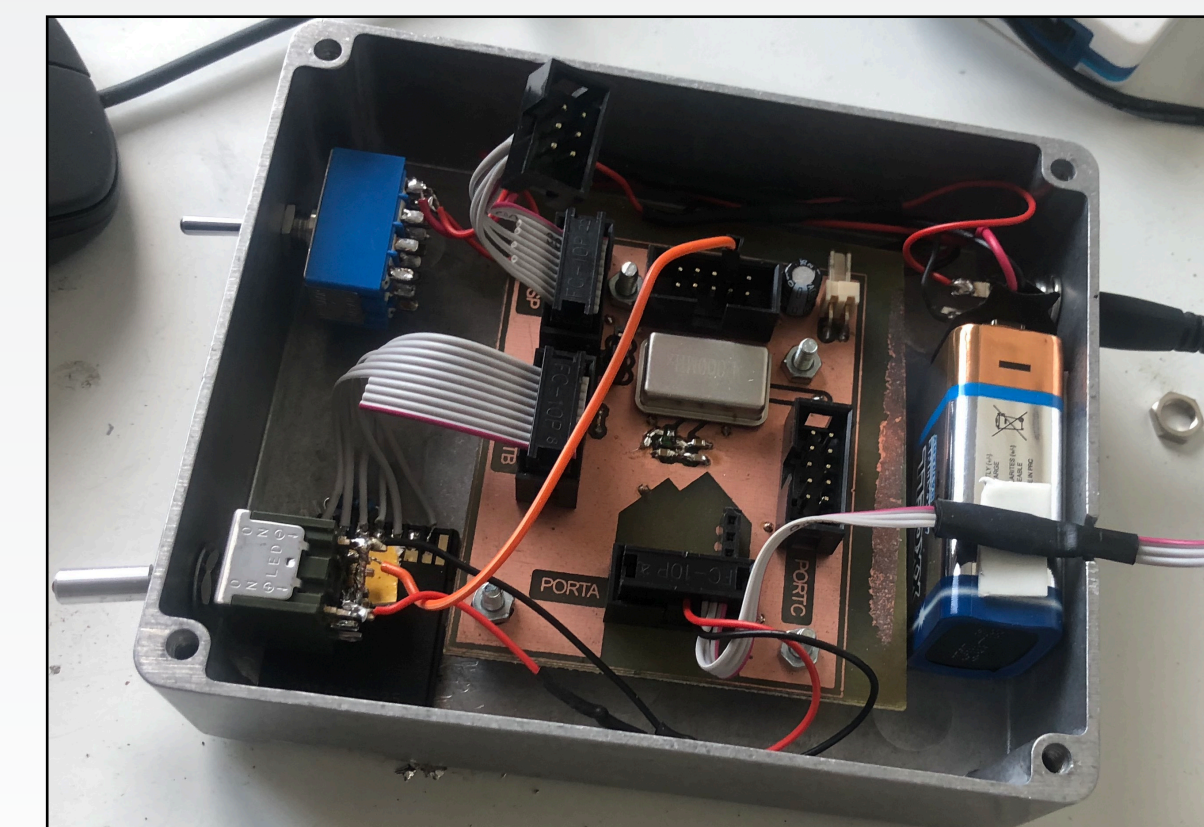
CV/IV: Annealing Steps

Step	Temperature °C	Time min	Eq. Time at RT days
1	60	10	3.8
2	60	20	6.9
3	60	40	13.3
4	60	80	27.9
5	60	100	53.7
6	60	140	100.0
7	80	25	203.1
8	80	57	407.4
9	80	120	824.1

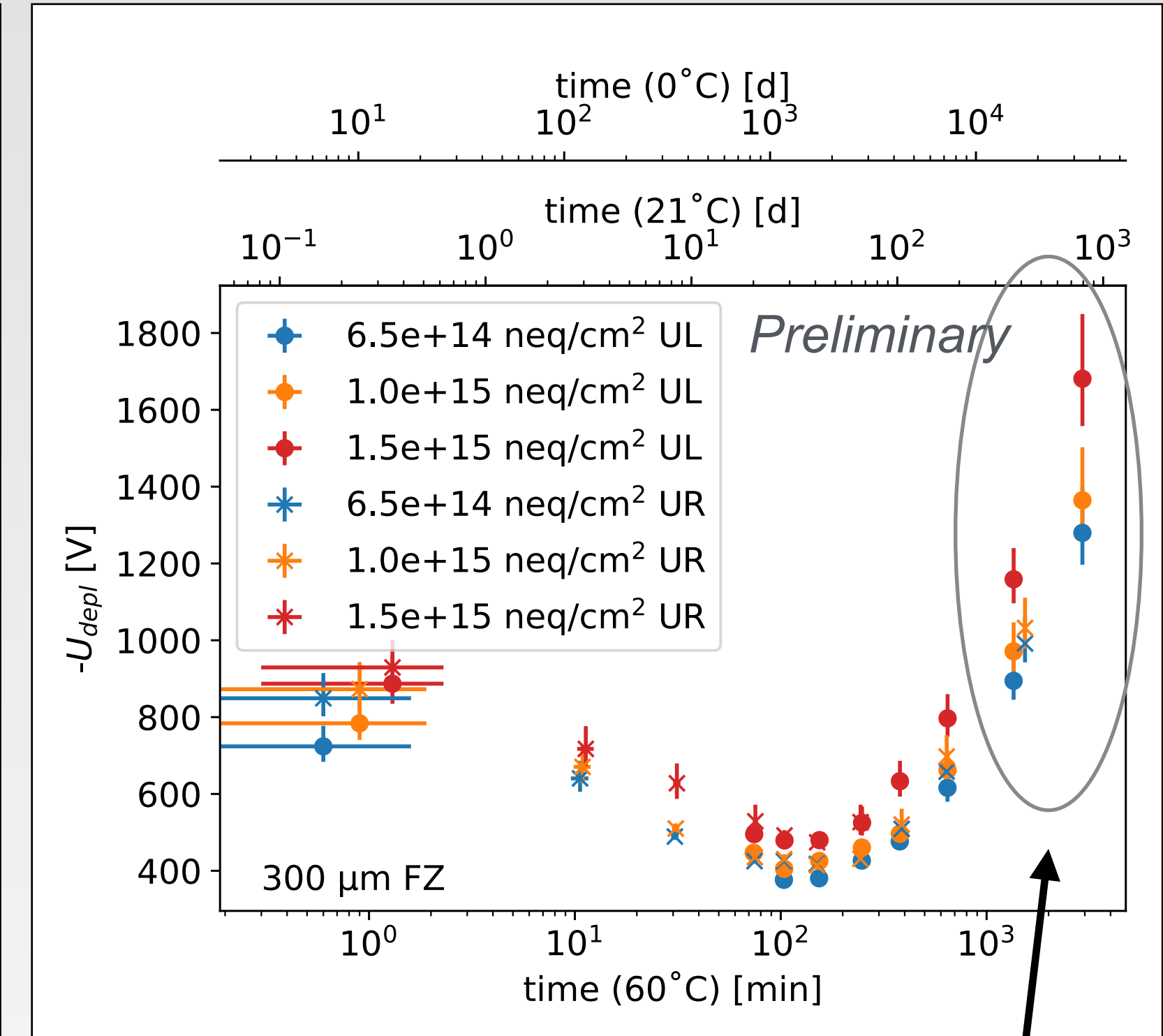
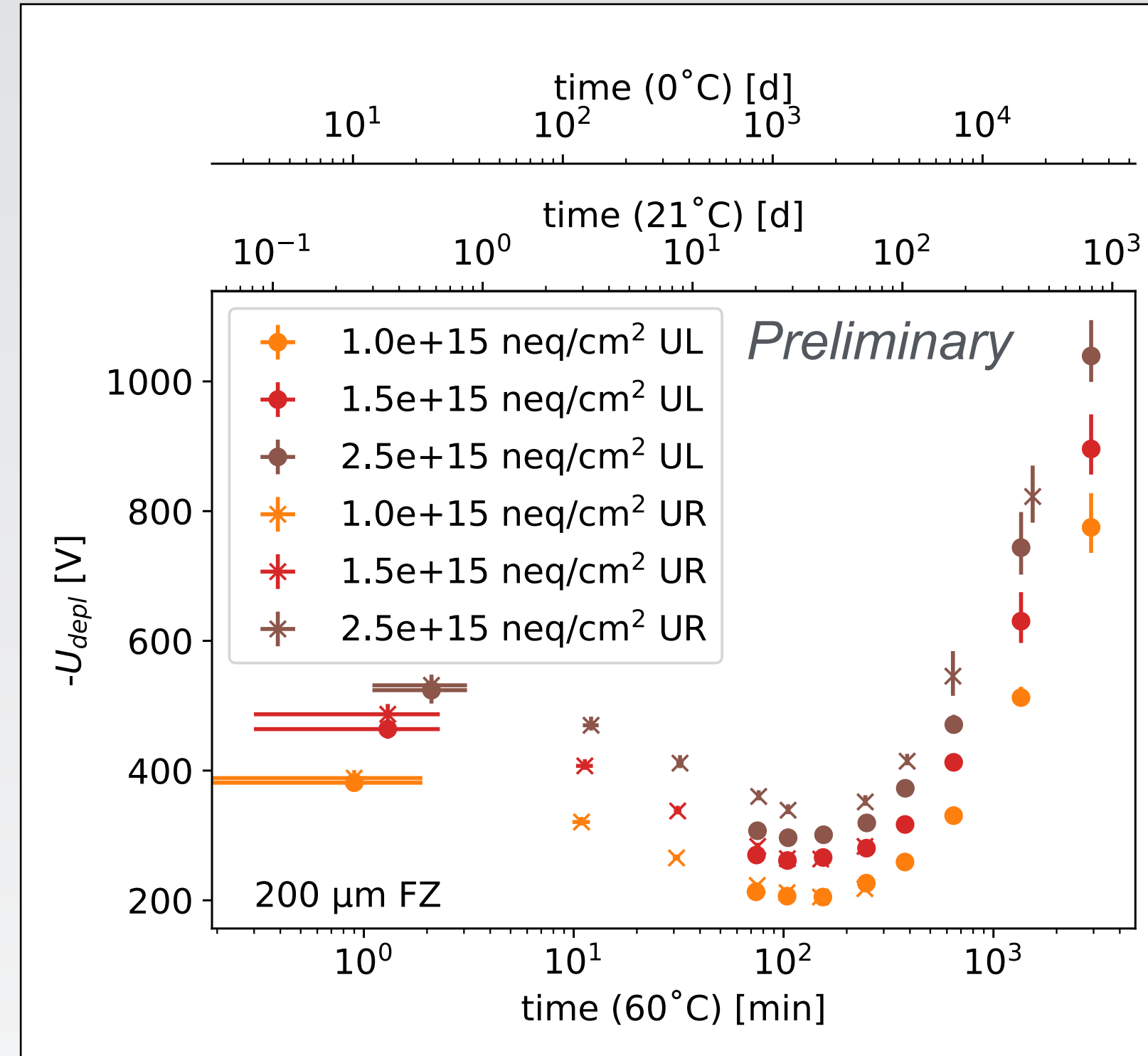
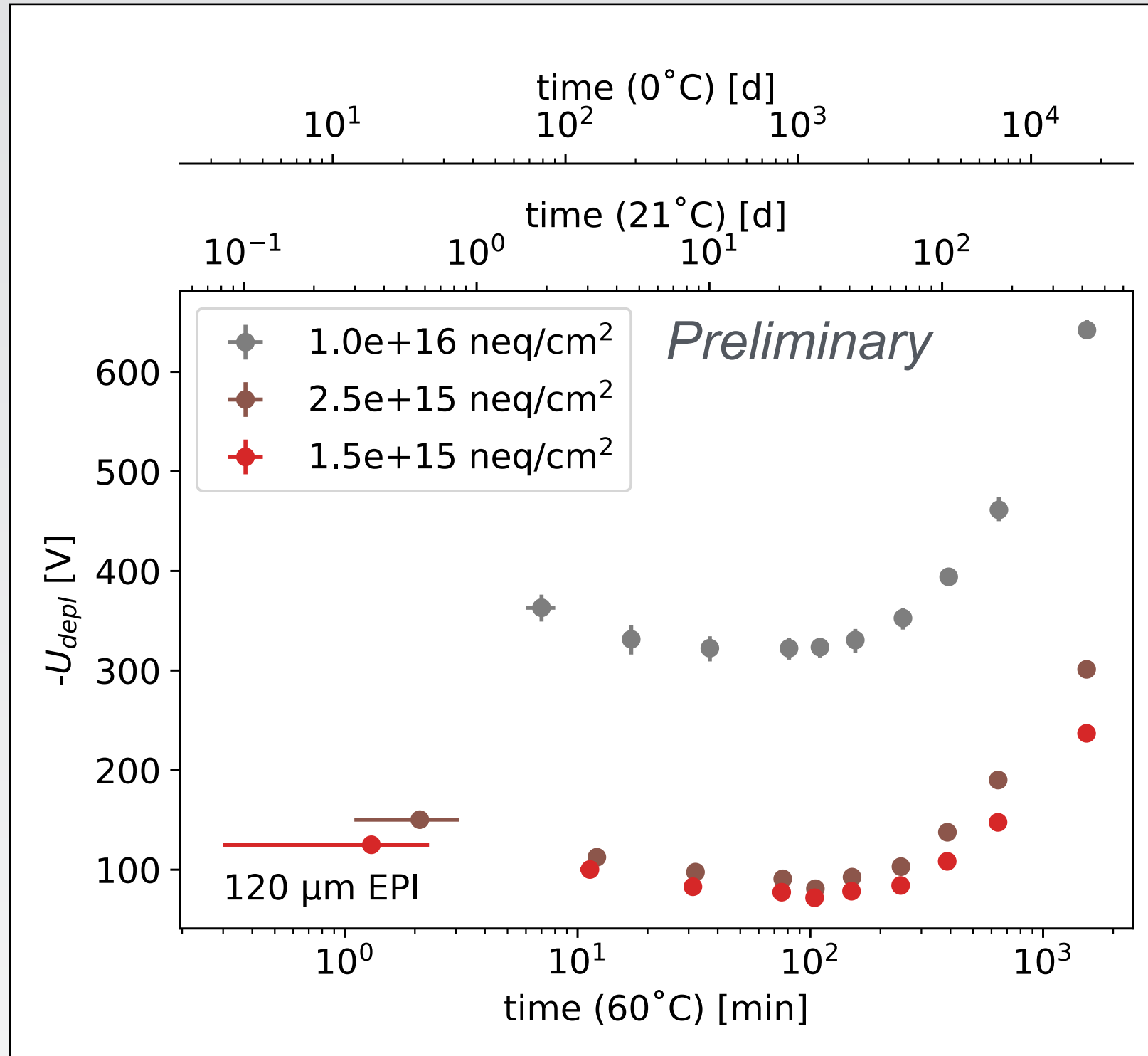
Δ step Cumulative at room temperature



- Target annealing times between 10 minutes and about 2000min at 60°C
- Anneal at 60°C up to about 400 minutes, then change to 80°C
- Temperature during annealing logged with 0.1°C accuracy
 - Target annealing time and actual annealing times differ slightly



Depletion voltage



- Samples with same fluence and thickness mostly compatible (taking into account 10% fluence uncertainty)
- Beneficial and reverse annealing clearly visible
- For EPI material, minimum consistent with about 80 minutes at 60°C
- For FZ material, minimum around 120 minutes at 60°C

Extrapolation region

Fit of depletion voltage vs. Annealing time

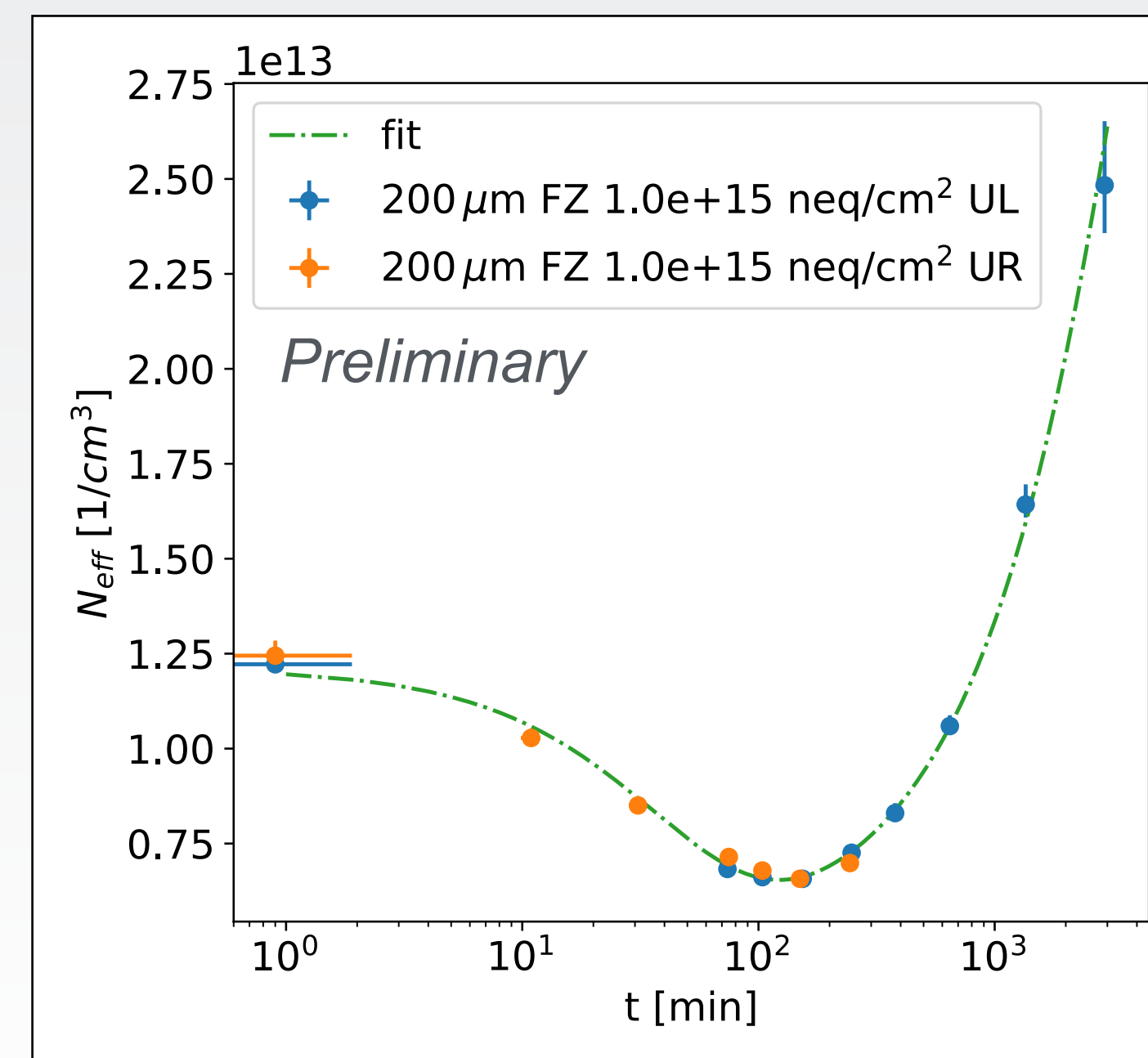
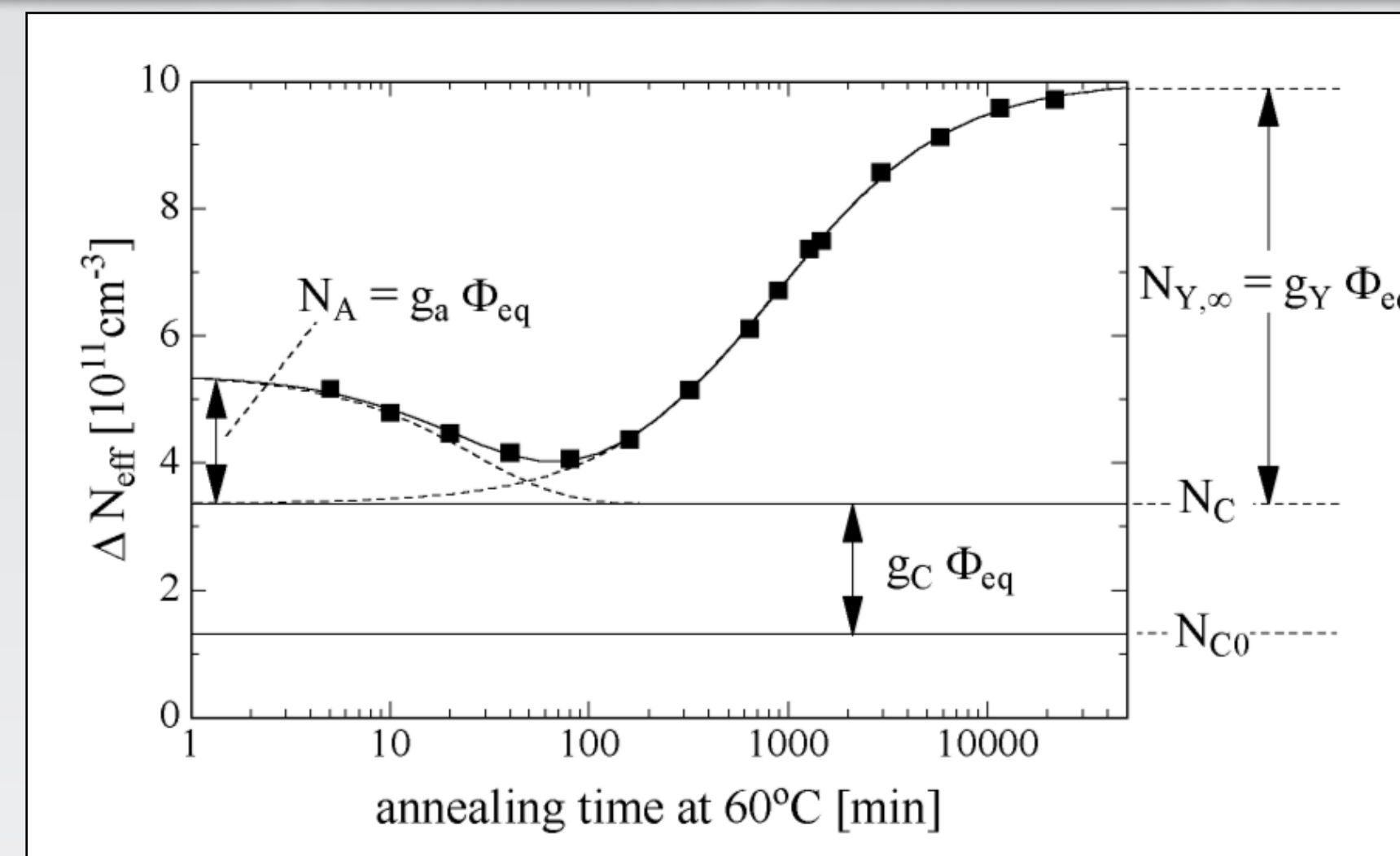
$$\Delta N_{eff}(\Phi_{eq}, t(T_a)) = N_A(\Phi_{eq}, t(T_a)) + N_C(\Phi_{eq}, t(T_a)) + N_Y(\Phi_{eq}, t(T_a)).$$

- Can be described by three terms
 - ▶ N_A : Beneficial annealing (exponentially falling)
 - ▶ Time constant τ_A
 - ▶ N_C : Constant radiation damage (here fitted as total constant offset: $N_C + N_{C0} + N_{Eff0}$)

- ▶ N_Y : reverse annealing:
 - ▶ Time constant τ_Y

$$N_{Y,\infty} \left(1 - \frac{1}{1 + t/\tau_Y} \right)$$

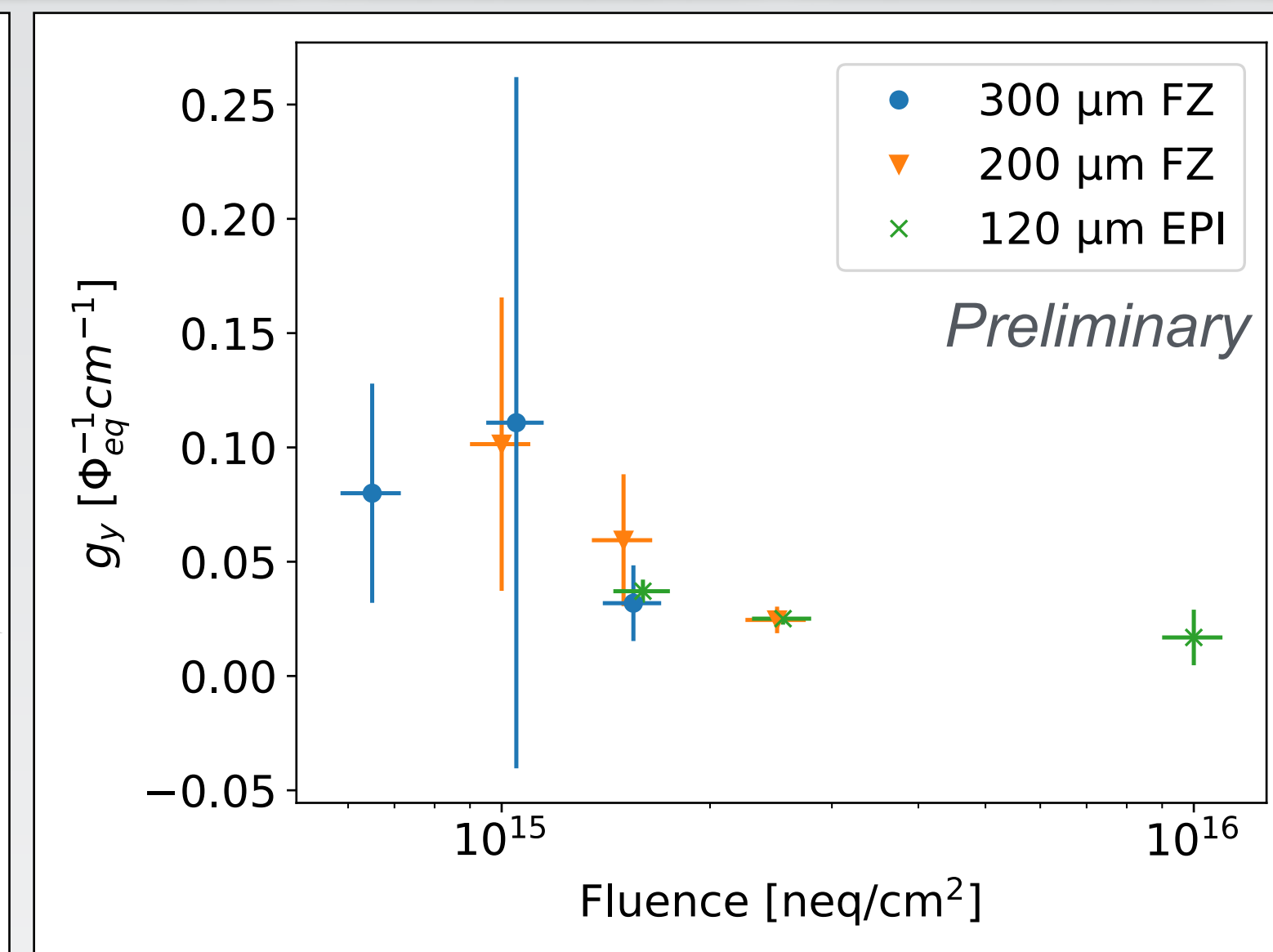
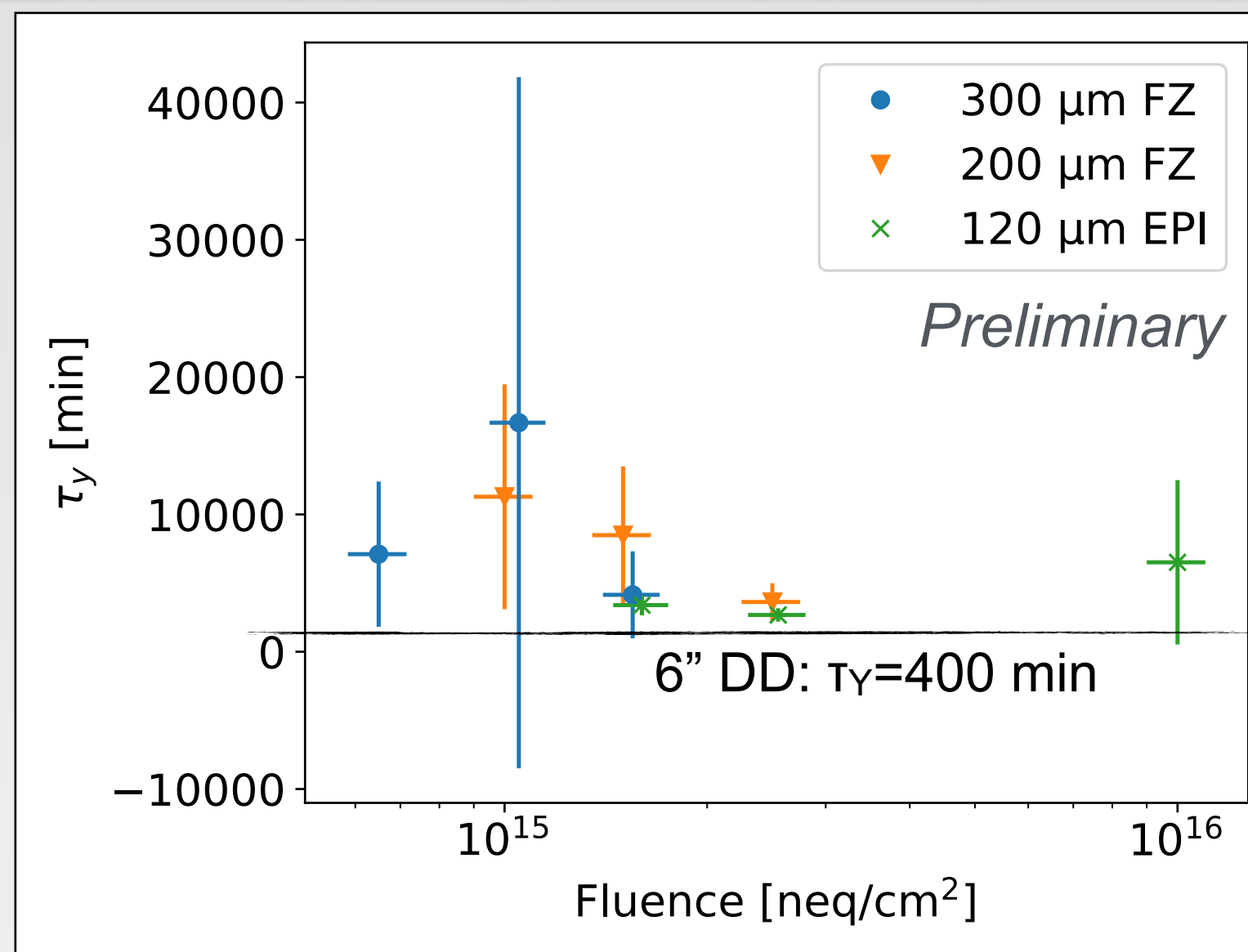
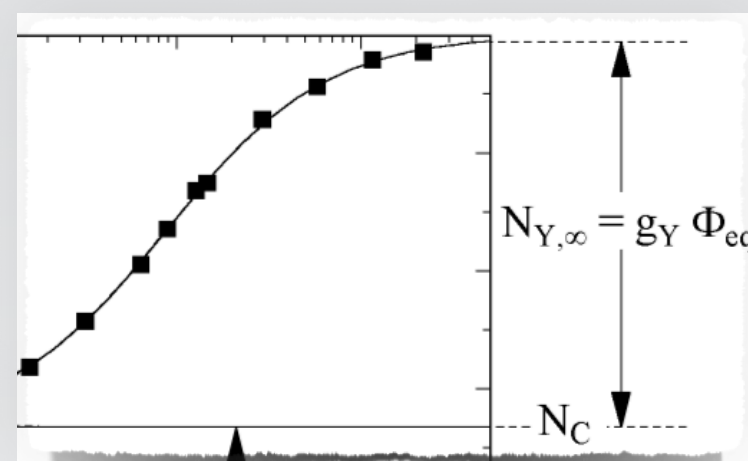
- Perform fit for each material and each fluence individually



Parametrisation of beneficial and reverse annealing

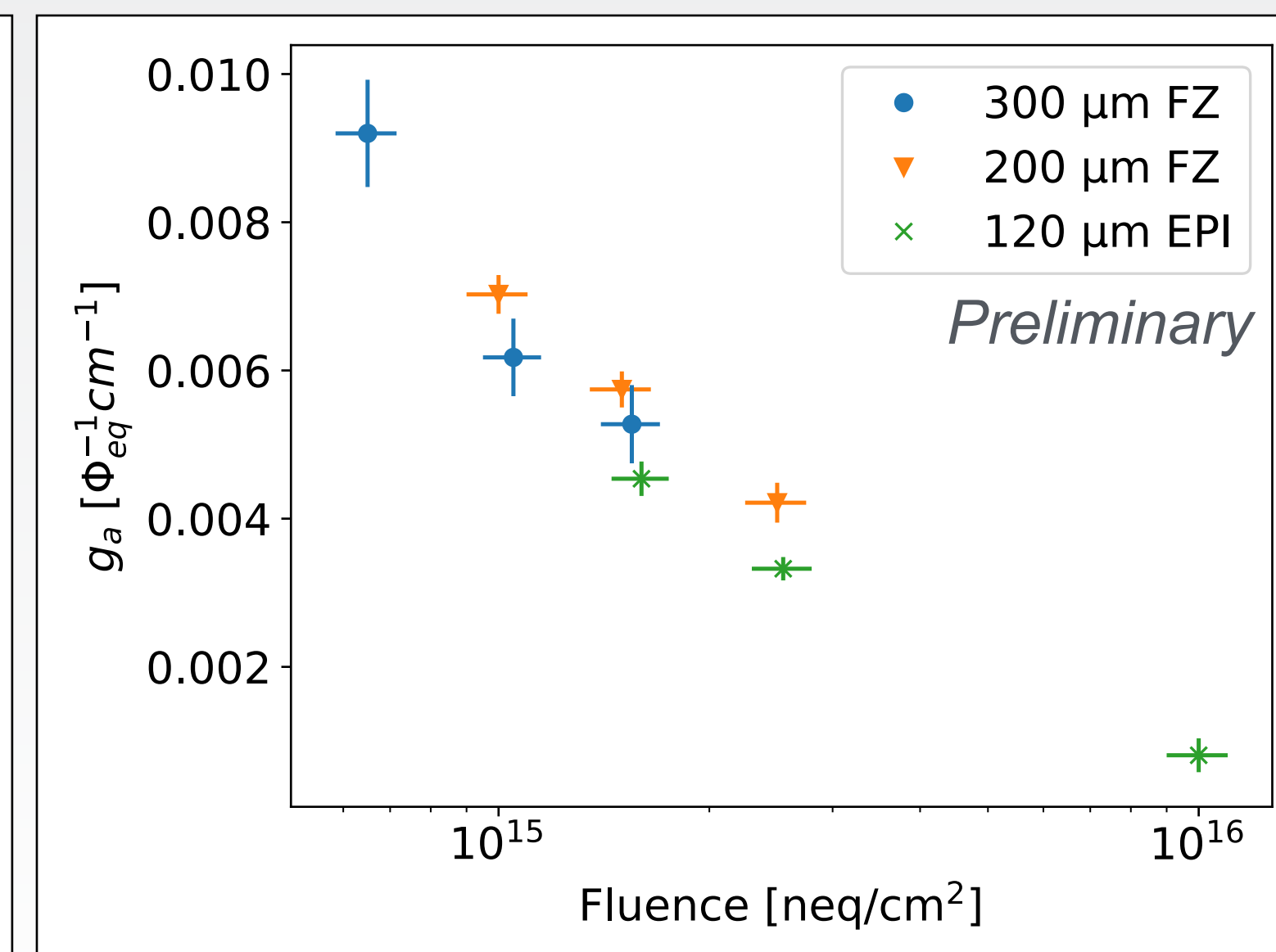
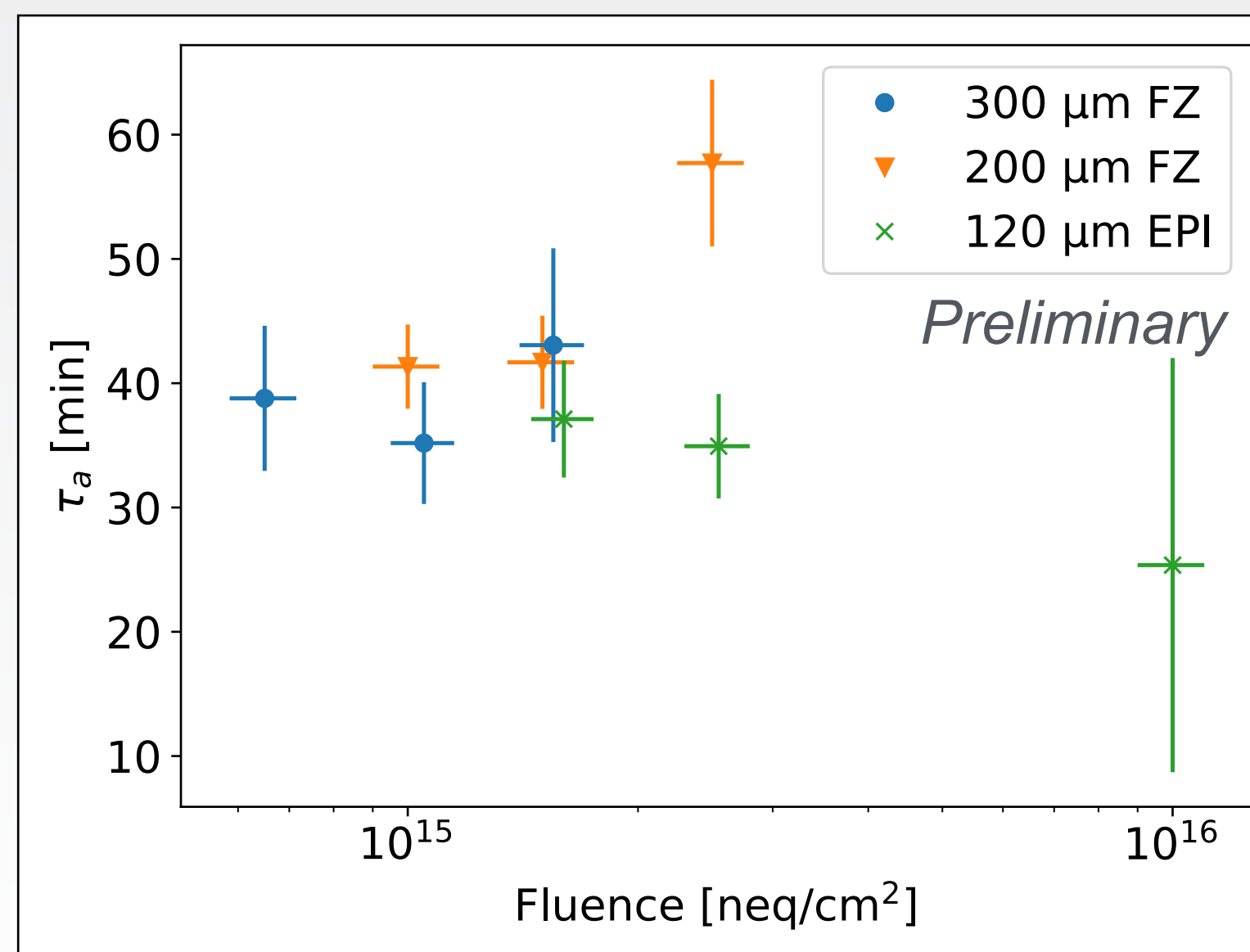
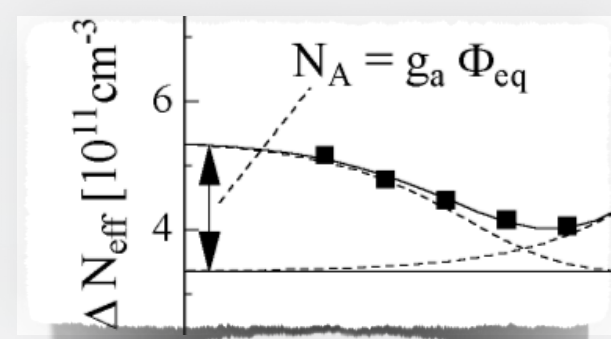
Reverse annealing

- Relatively large uncertainties
 - Not enough points at long annealing times
- Relatively large timing constant
- Slow reverse annealing compared to 6" DD sample
- g_Y almost constant as expected

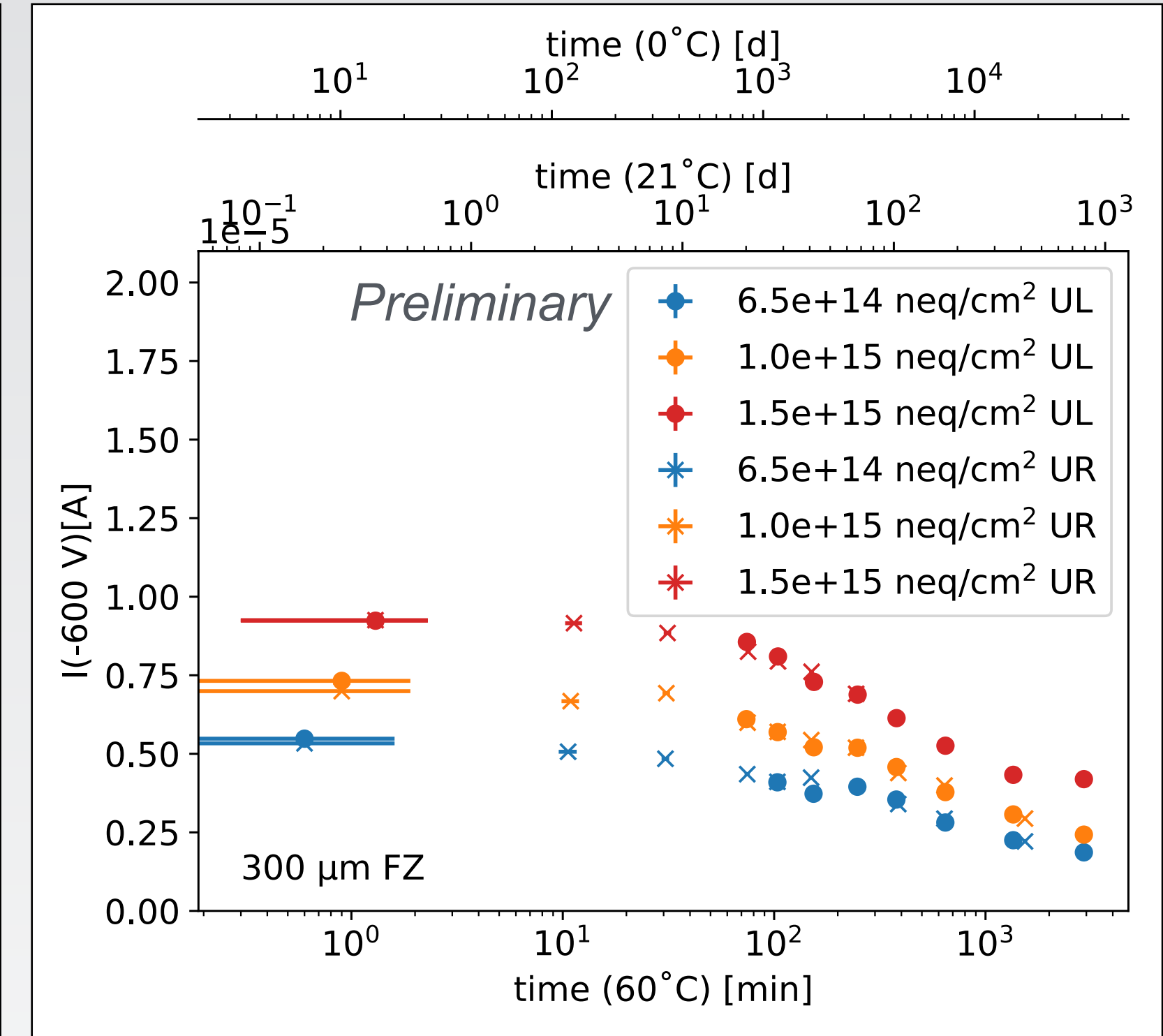
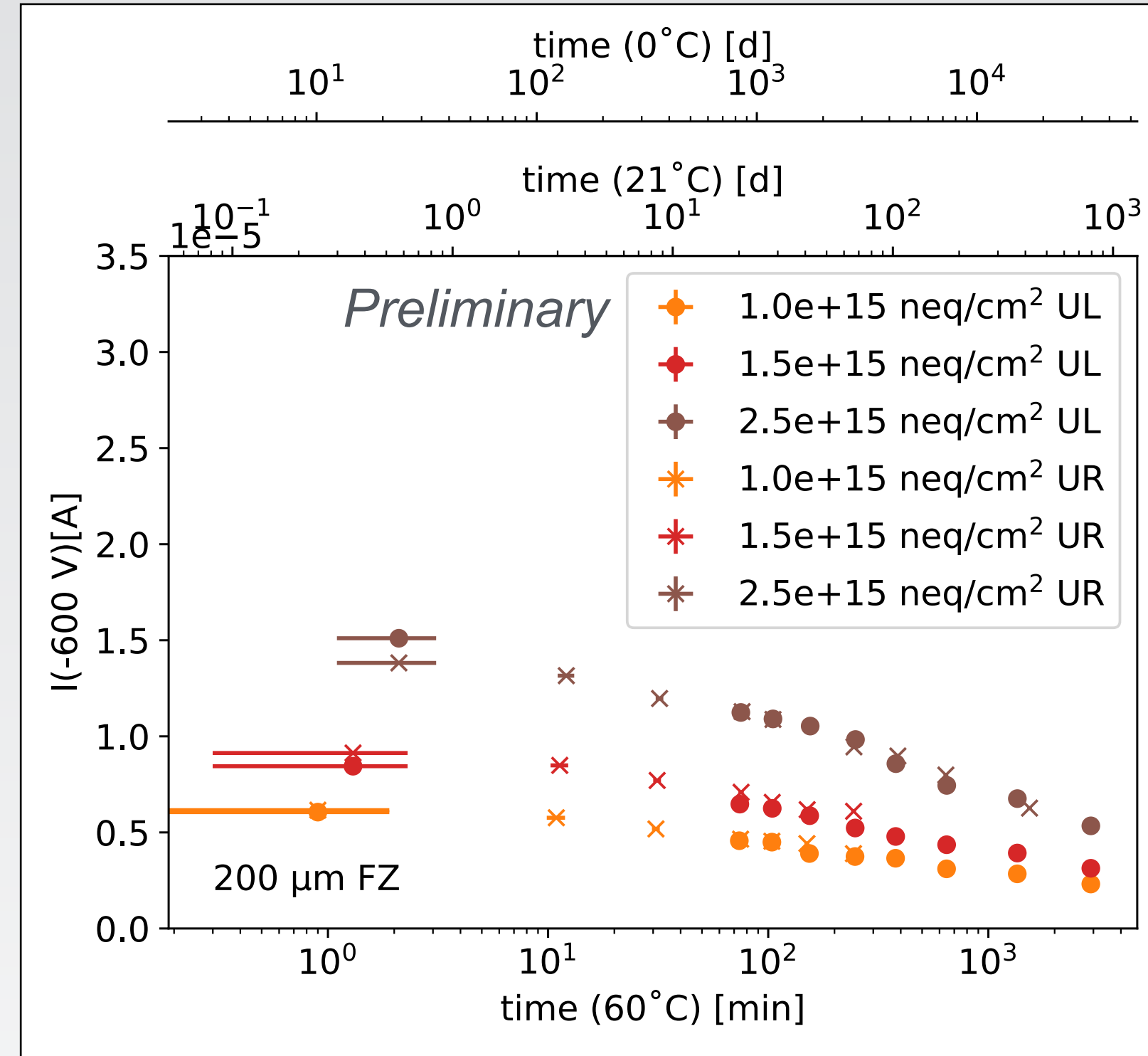
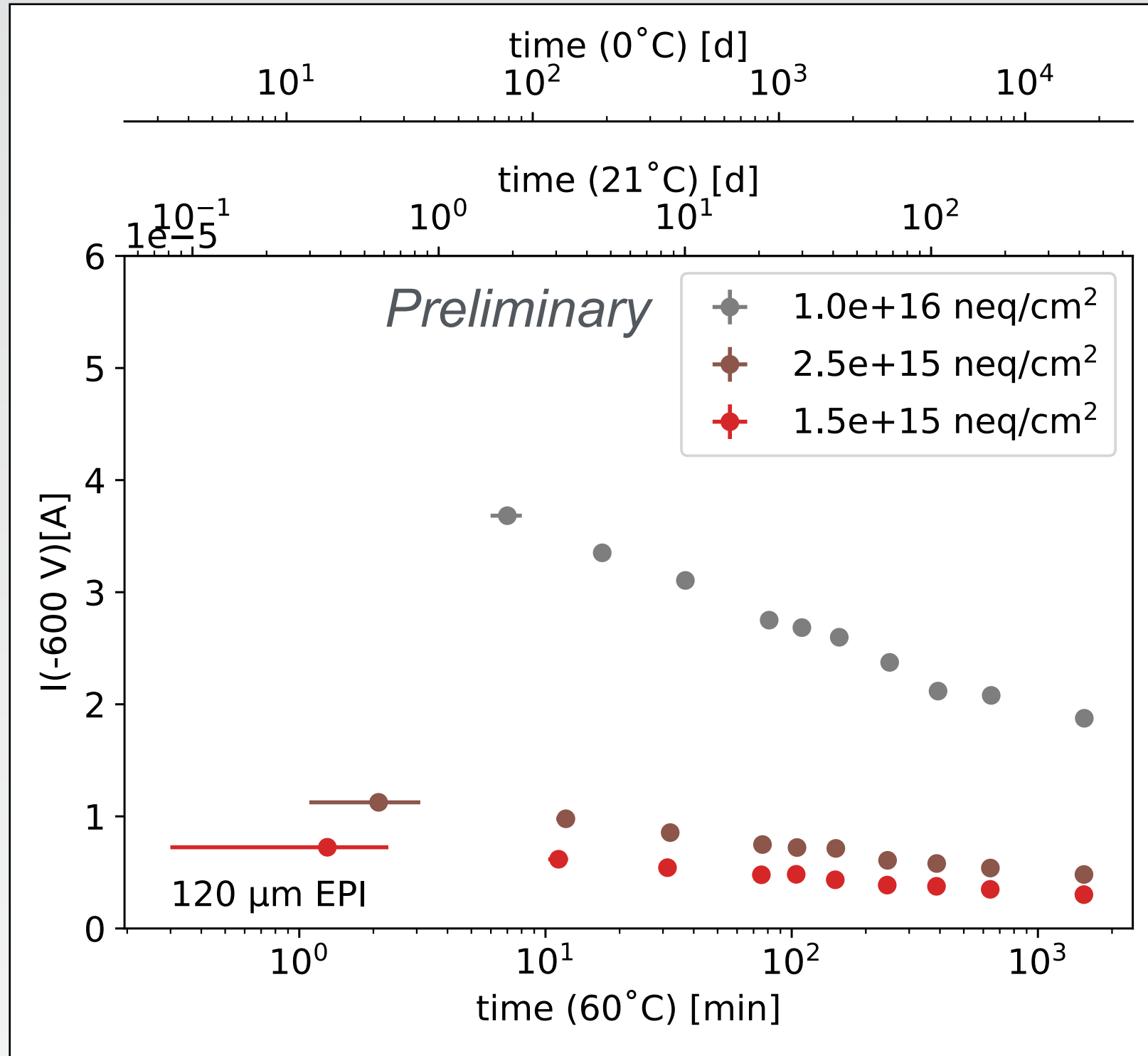


Beneficial annealing

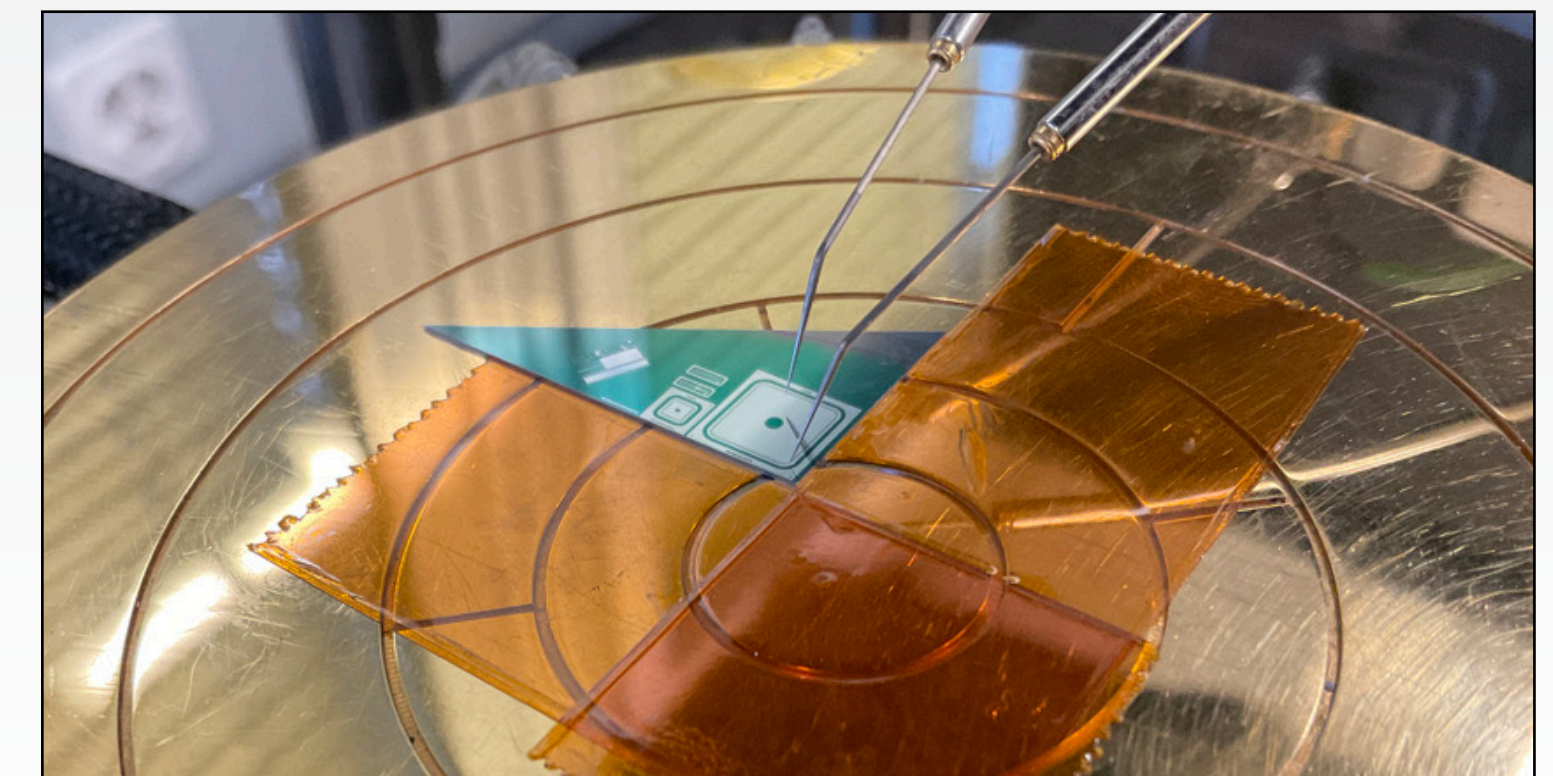
- Timing constant shows some spread
- Clear unexpected dependence of g_a on fluence contrary to constant expectation
 - Needs to be investigated



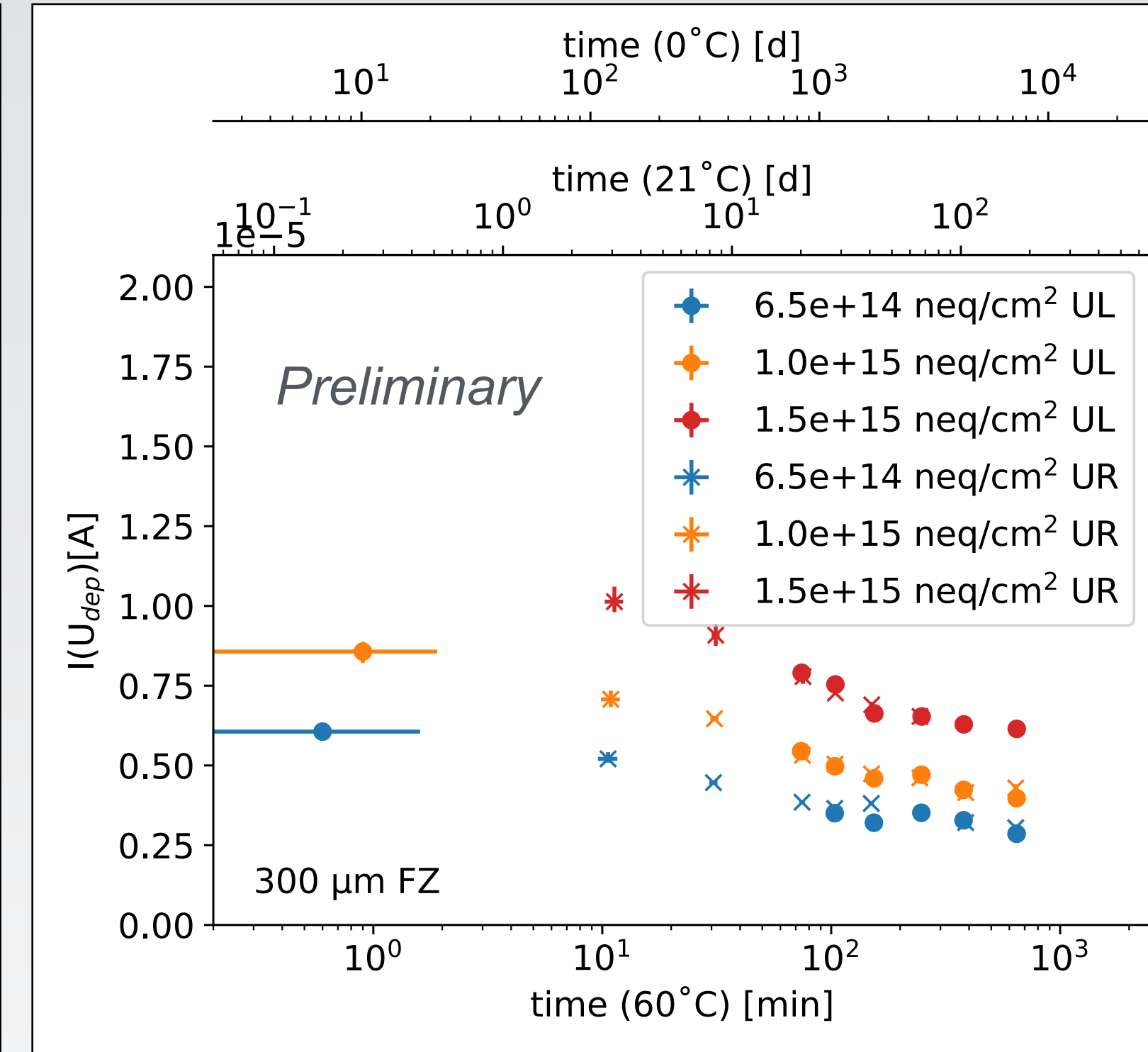
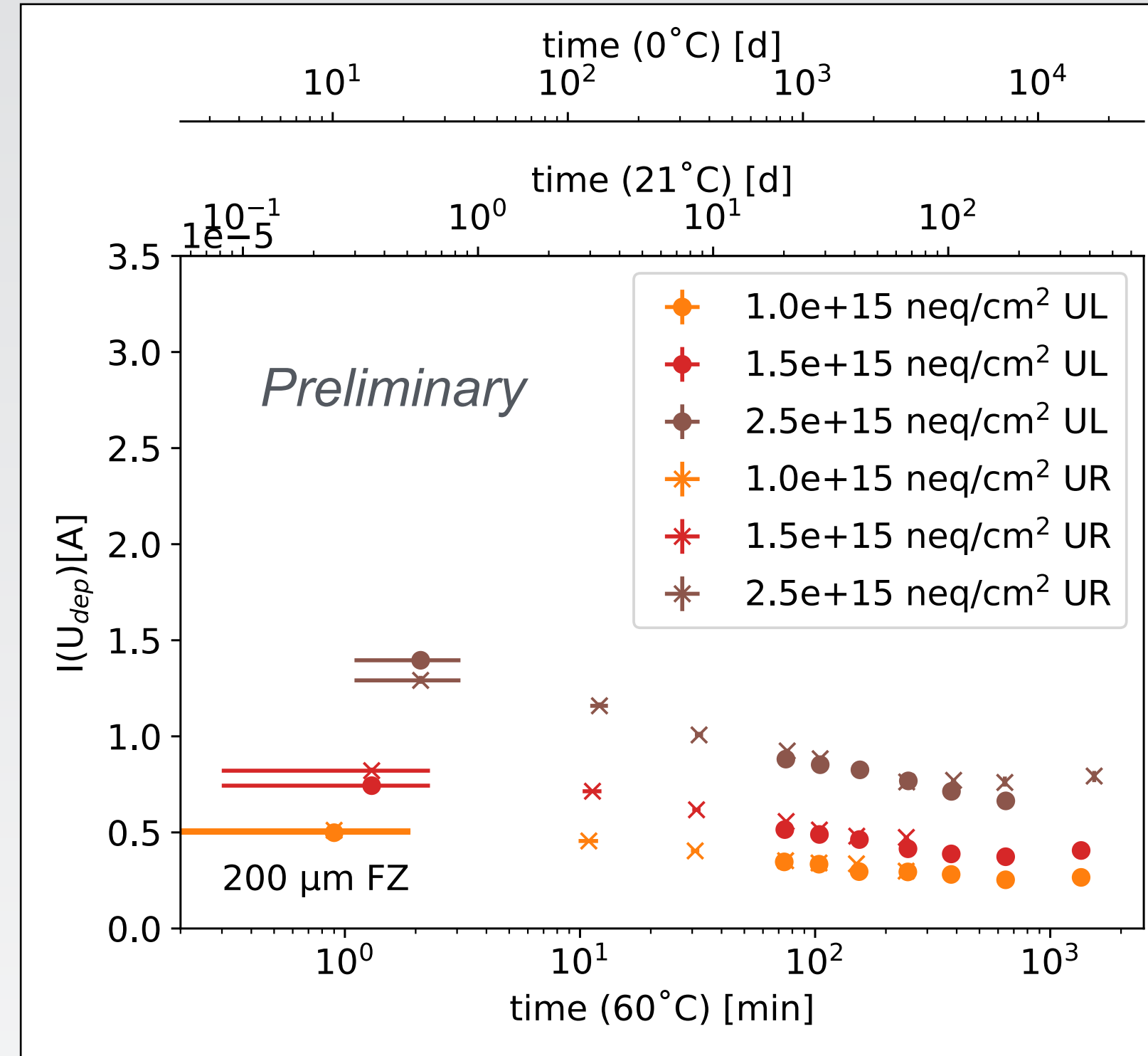
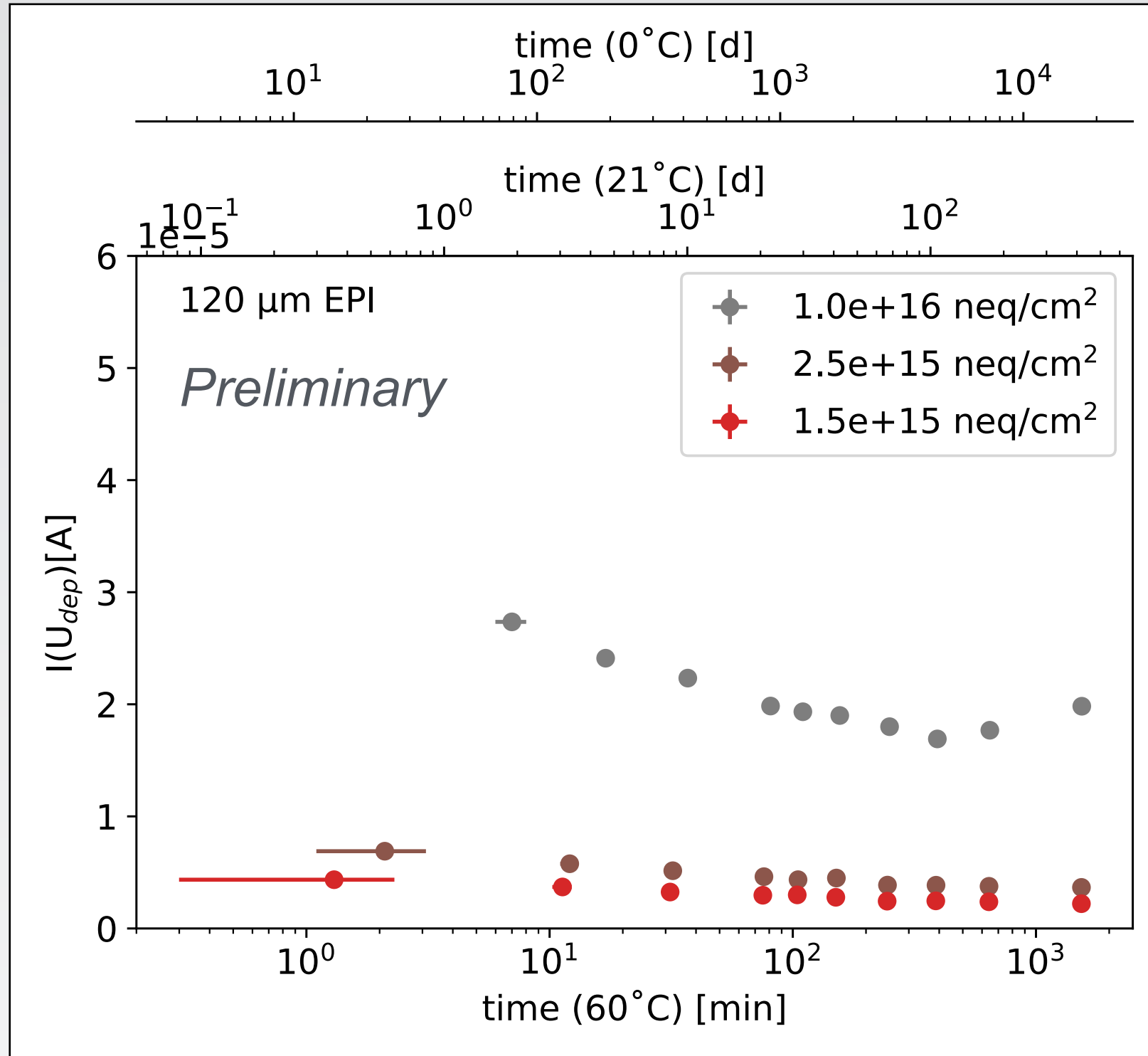
Leakage current



- Leakage current of the order of 10μA at -20°C
- Samples with same fluence and thickness mostly compatible (taking into account 10% fluence uncertainty)
- Exponentially falling current (slight deviation for 300μm sensors)

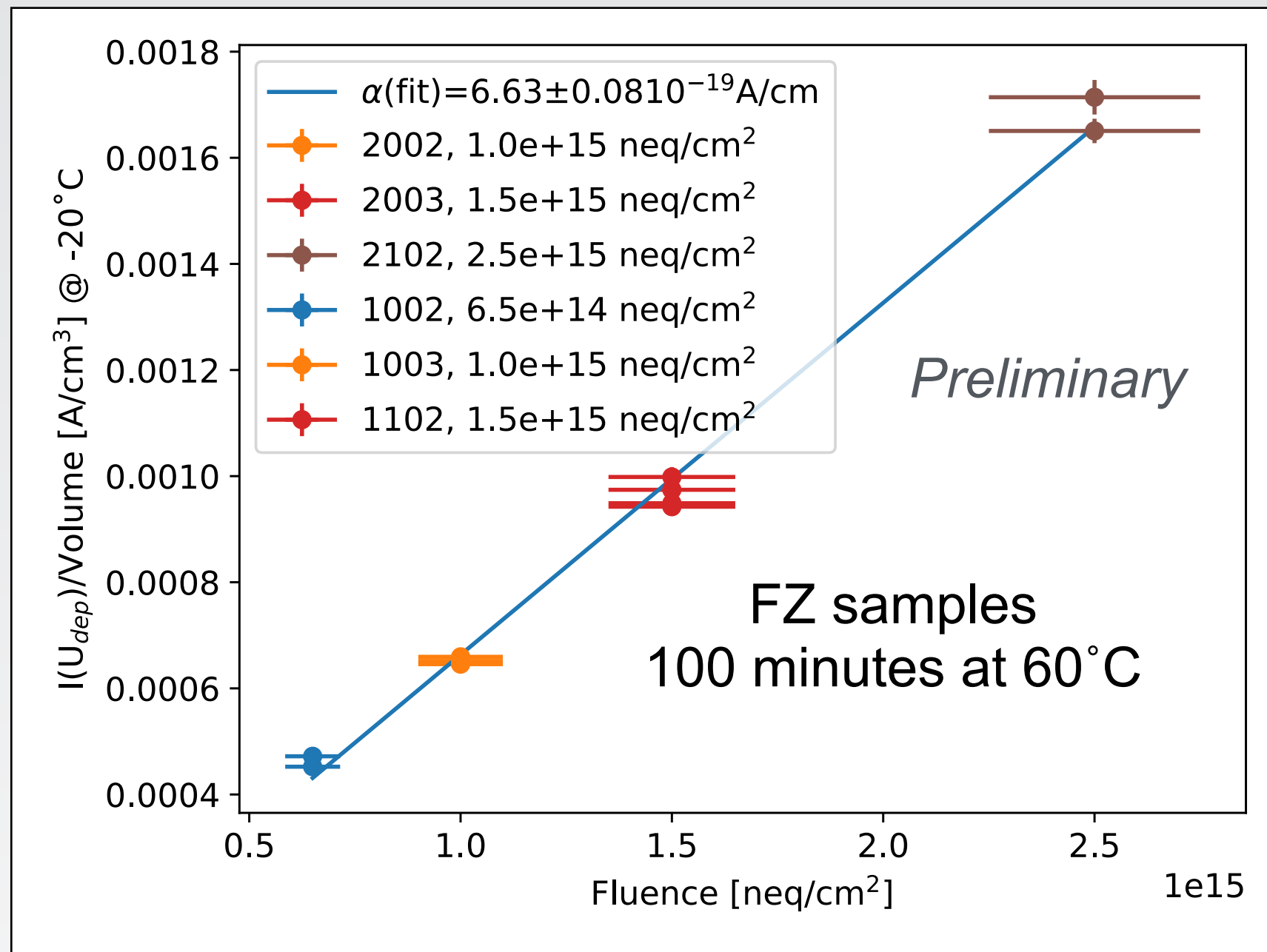


Extraction of α

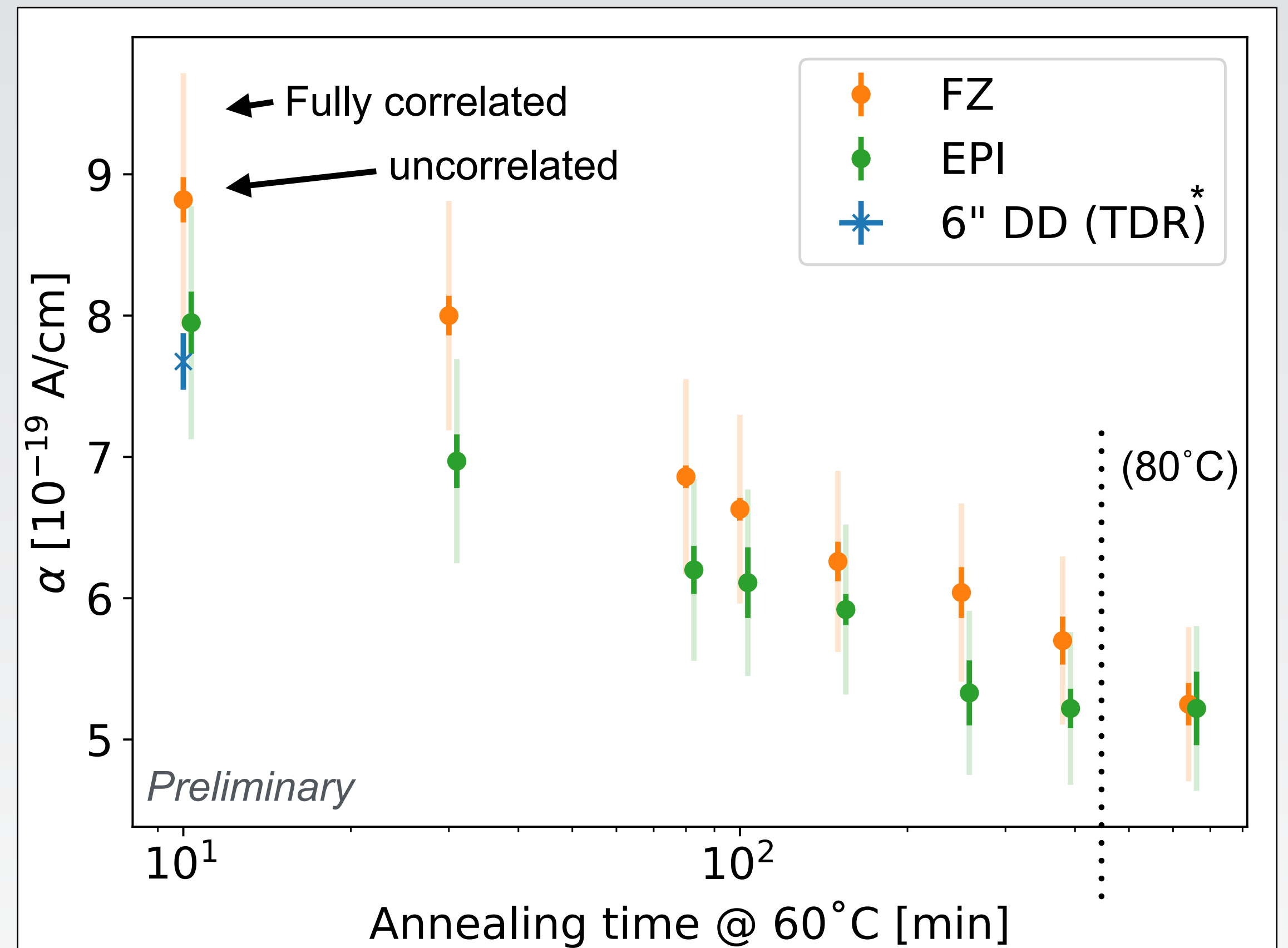


- $I(U_{dep}) / \text{thickness}$ is a proxy for the slope of α
 - ▶ Should be universal, and not depend on thickness/diode type
 - ▶ Interpolation and smoothing of measured leakage current
- Mostly consistent picture, reverse annealing impact for large annealing time

α Fit



x16

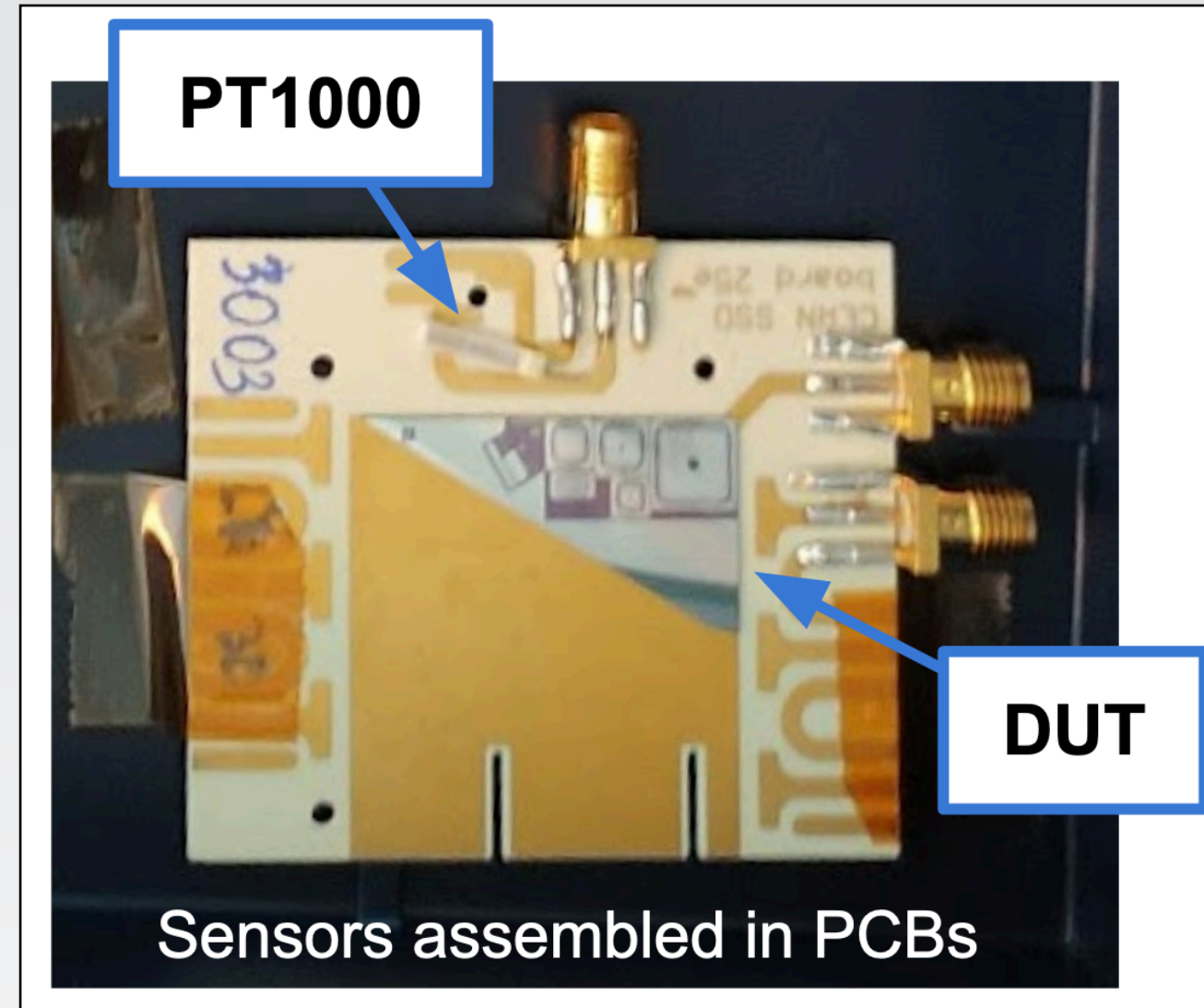


- Uncertainties from depletion voltage, time, and leakage current fully propagated
- Large uncertainty spread depending on the correlation of fluence uncertainties
- Expected exponential decay up to 600 minutes equivalent annealing time at 60°C

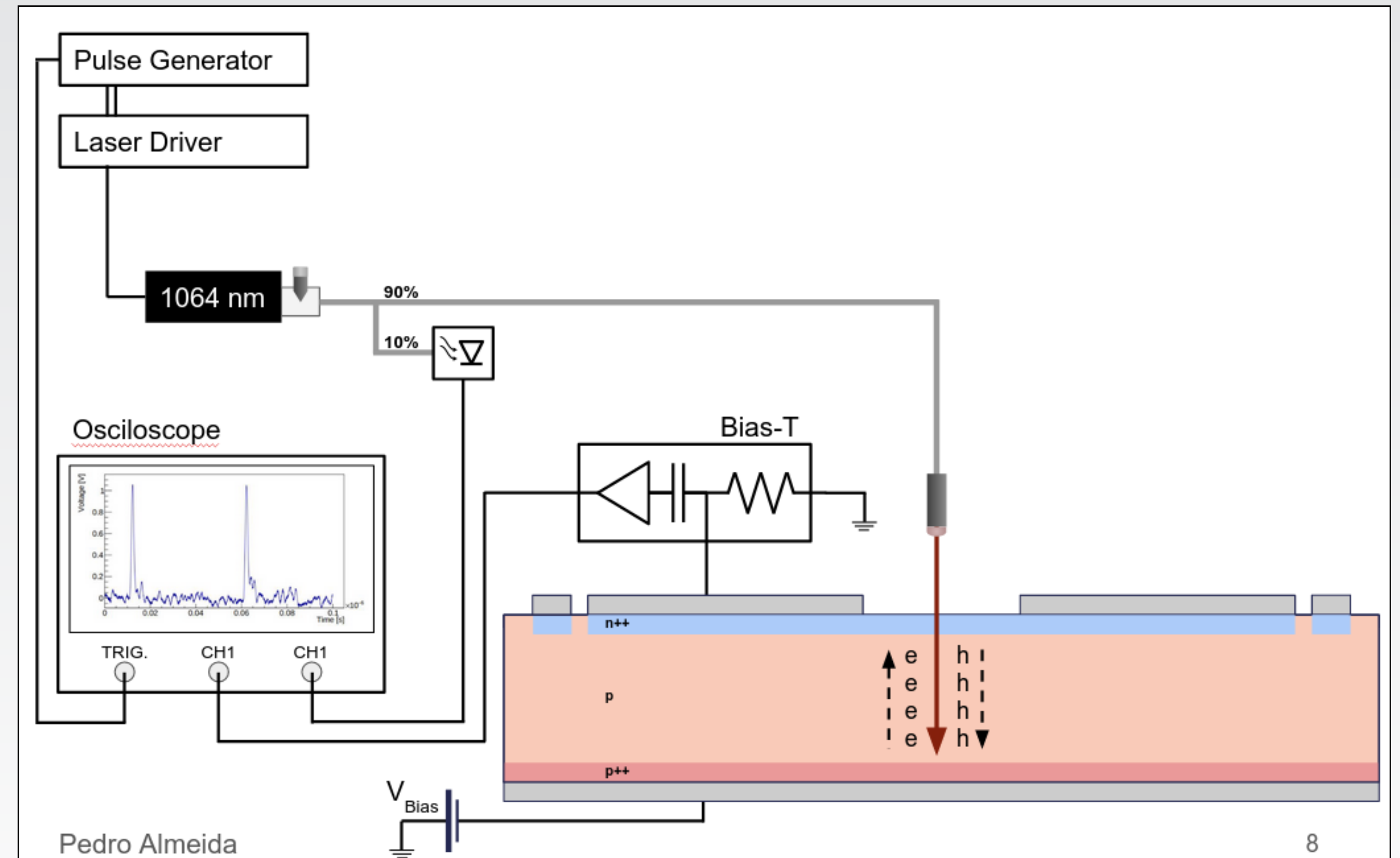
- Compatible with previous studies from the HGCal technical design report:
- Difference of 20% (understood) +20% (to be understood) w.r.t. full wafer measurements

*CERN-LHCC-2017-023

Charge Collection Efficiency

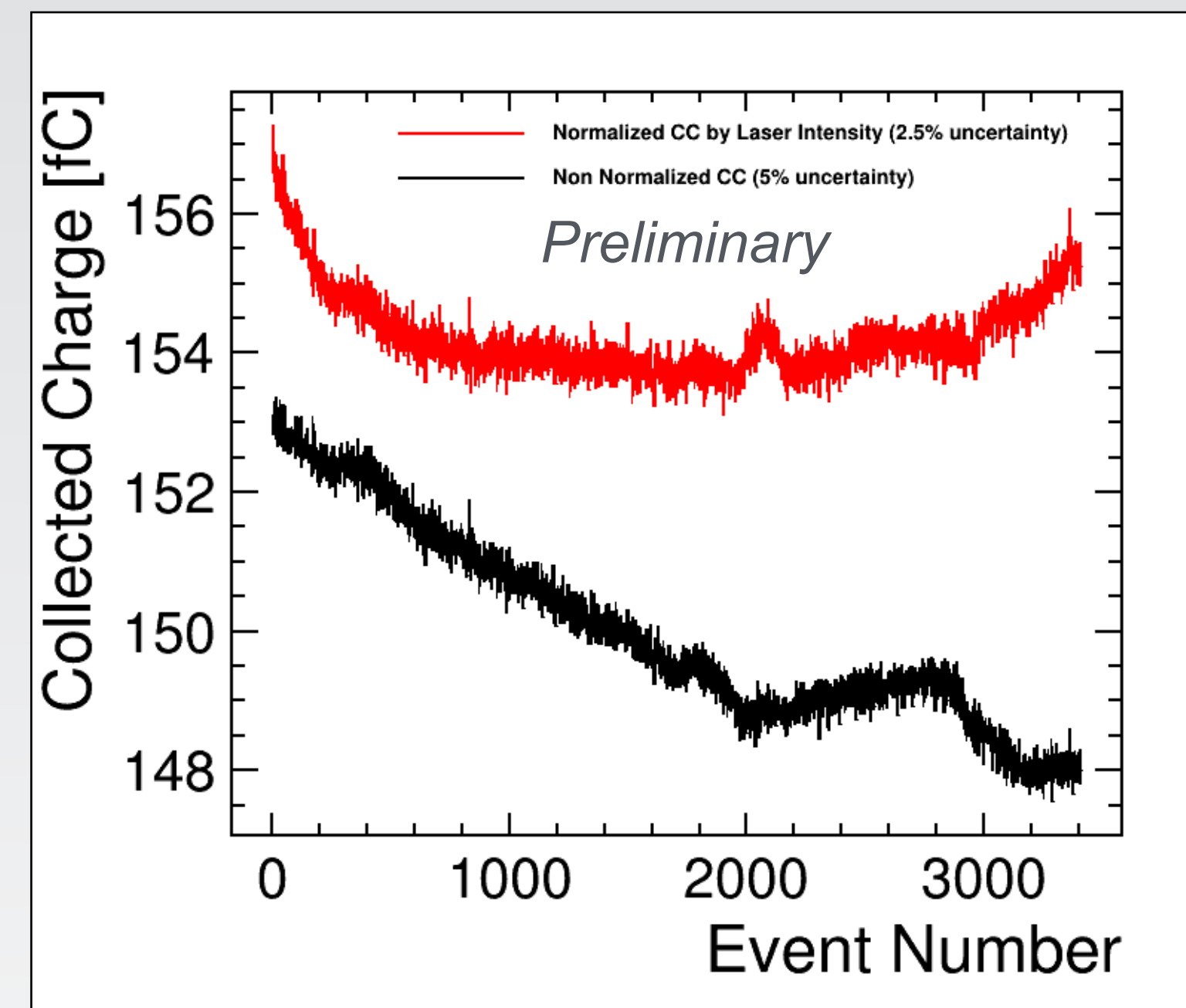
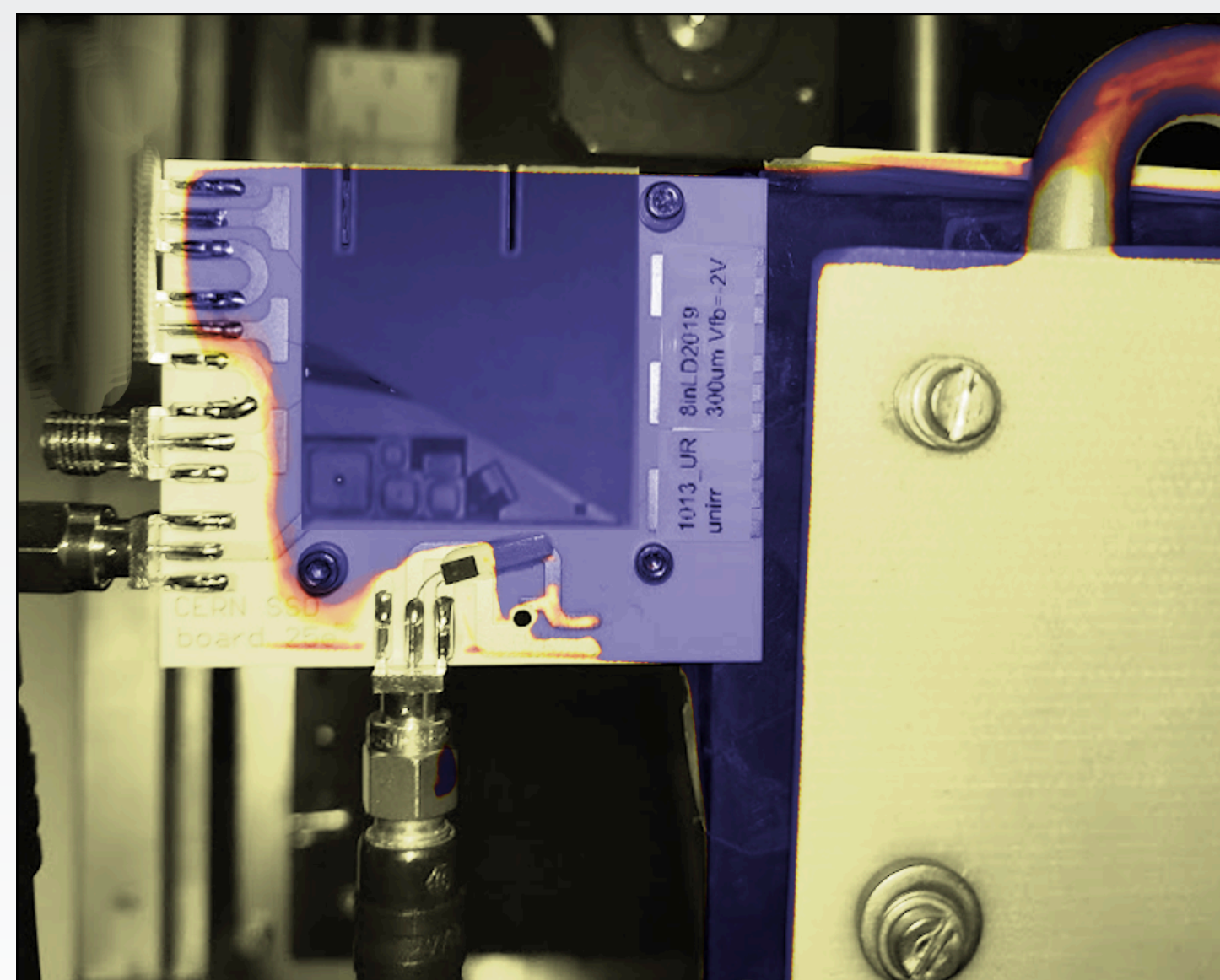


- 12 samples
 - ▶ Same fluences as CV/IV measurements
- 6 Annealing points
- Sensors assembled on PCB + wire bonded
- Laser intensity about 33 MIPs (300 μ m sensor)

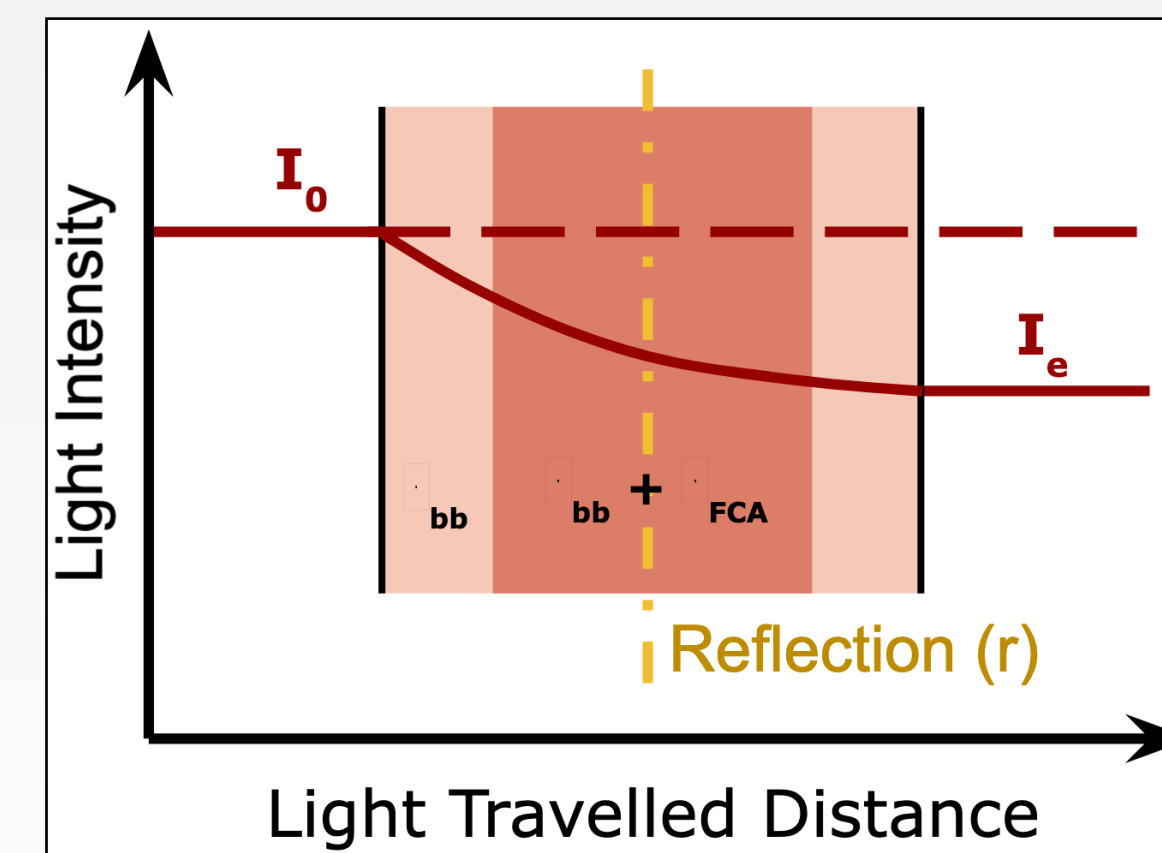


Uncertainties and corrections

- Drifts in the (not temperature controlled) reference diode
 - Calibrated over long measurement period with reference sensor
 - Assign 2.5% uncertainty
- Temperature across the PCB, in particular close to PT1000
 - Uncertainty +1 -5°C
- Absorption depends on temperature [1]
 - Uncertainty of -1.8% + 7.1% in the charge collection

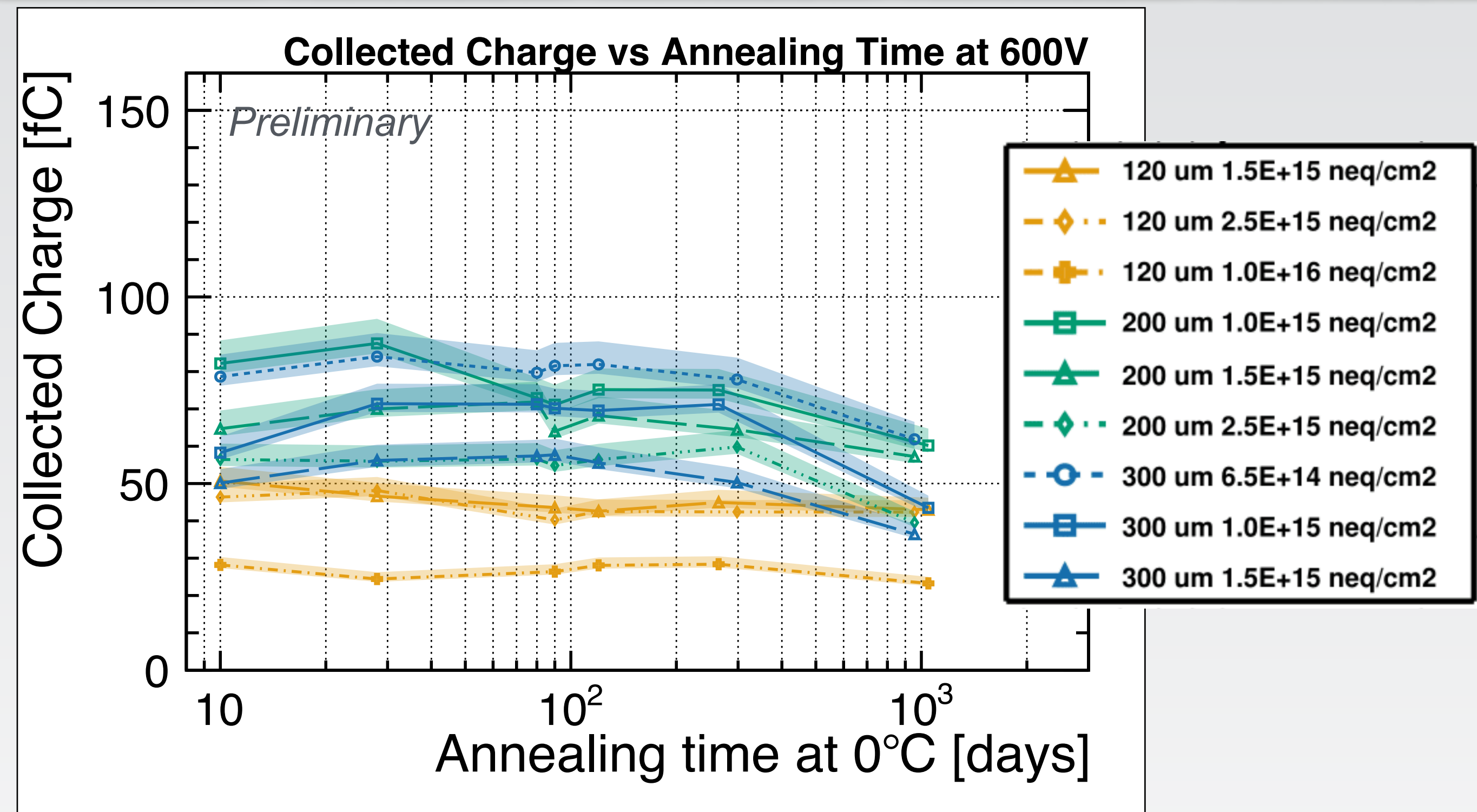
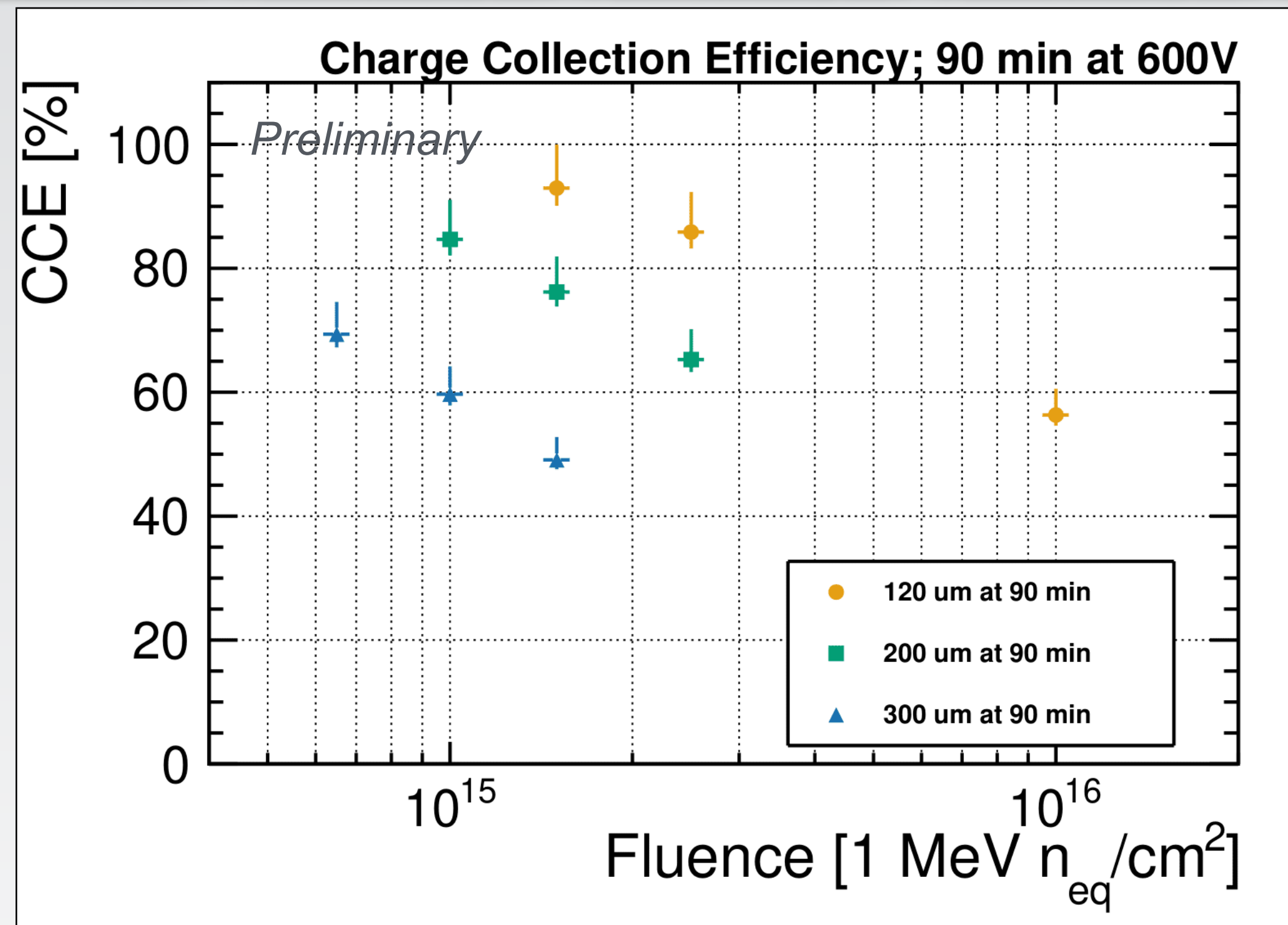


- Laser attenuation and reflection on backside
- Corrected for in results
- Associated uncertainties negligible



[1] Schinke et al.

Results



- Charge collection efficiency decreases with fluence
- Charge collection efficiency ~50% or higher at 600V for all fluences (approx +10% at 800V)
- No significant dependence on annealing time

Summary



- An extensive annealing study on diodes from 8" wafers has been carried out
 - ▶ About 150 measurements of capacitance and leakage current
 - ▶ About 70 measurements to determine charge collection efficiencies

- Depletion voltage minimum seems to be around 120 minutes of annealing at 60°C for FZ
 - ▶ Slightly lower for highly irradiated EPI material
- Seemingly slow reverse annealing

- Charge collection efficiencies (way) above 50% for all fluences
 - ▶ Working on cross-checks with Sr90 source

- No significant dependence or degradation with annealing time

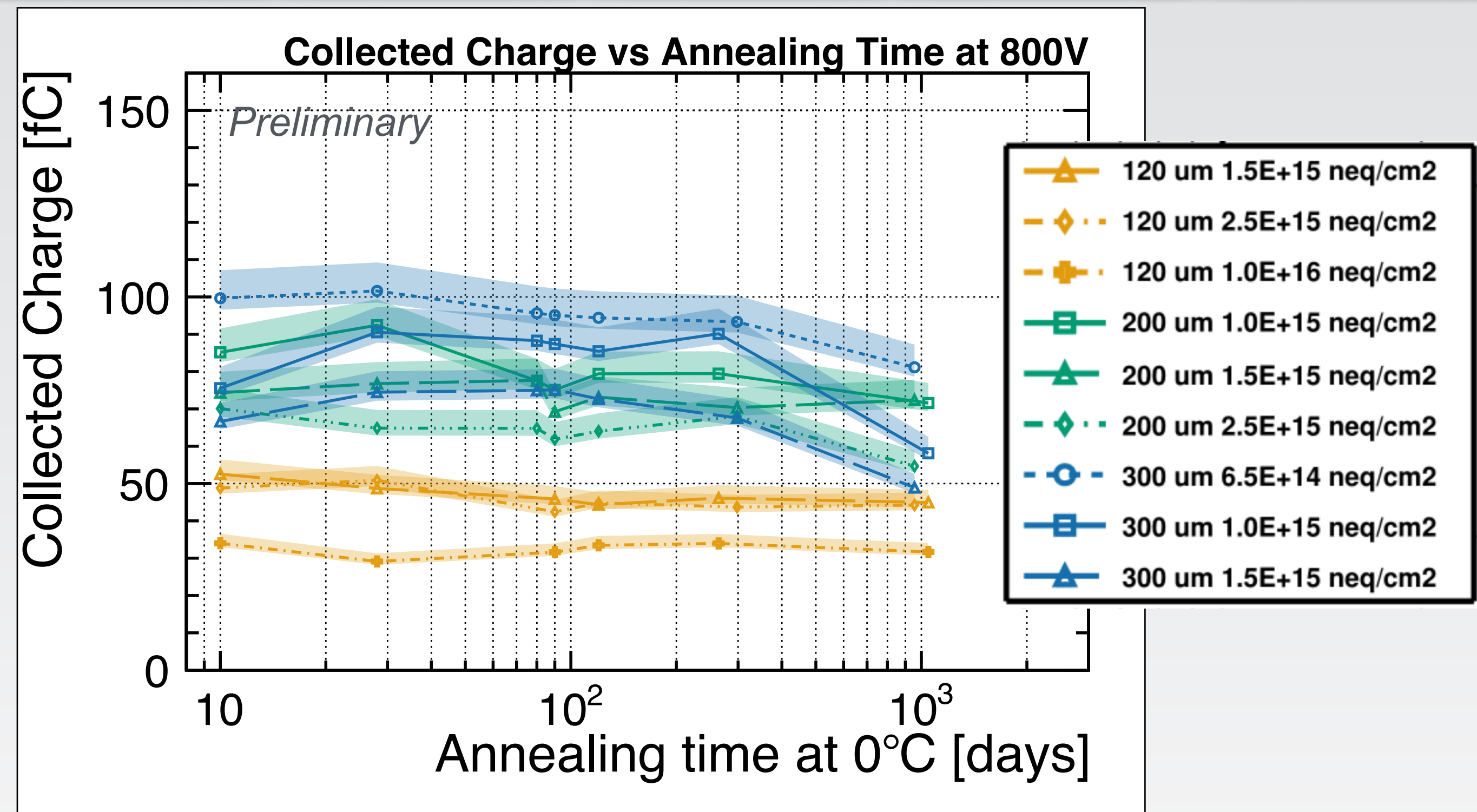
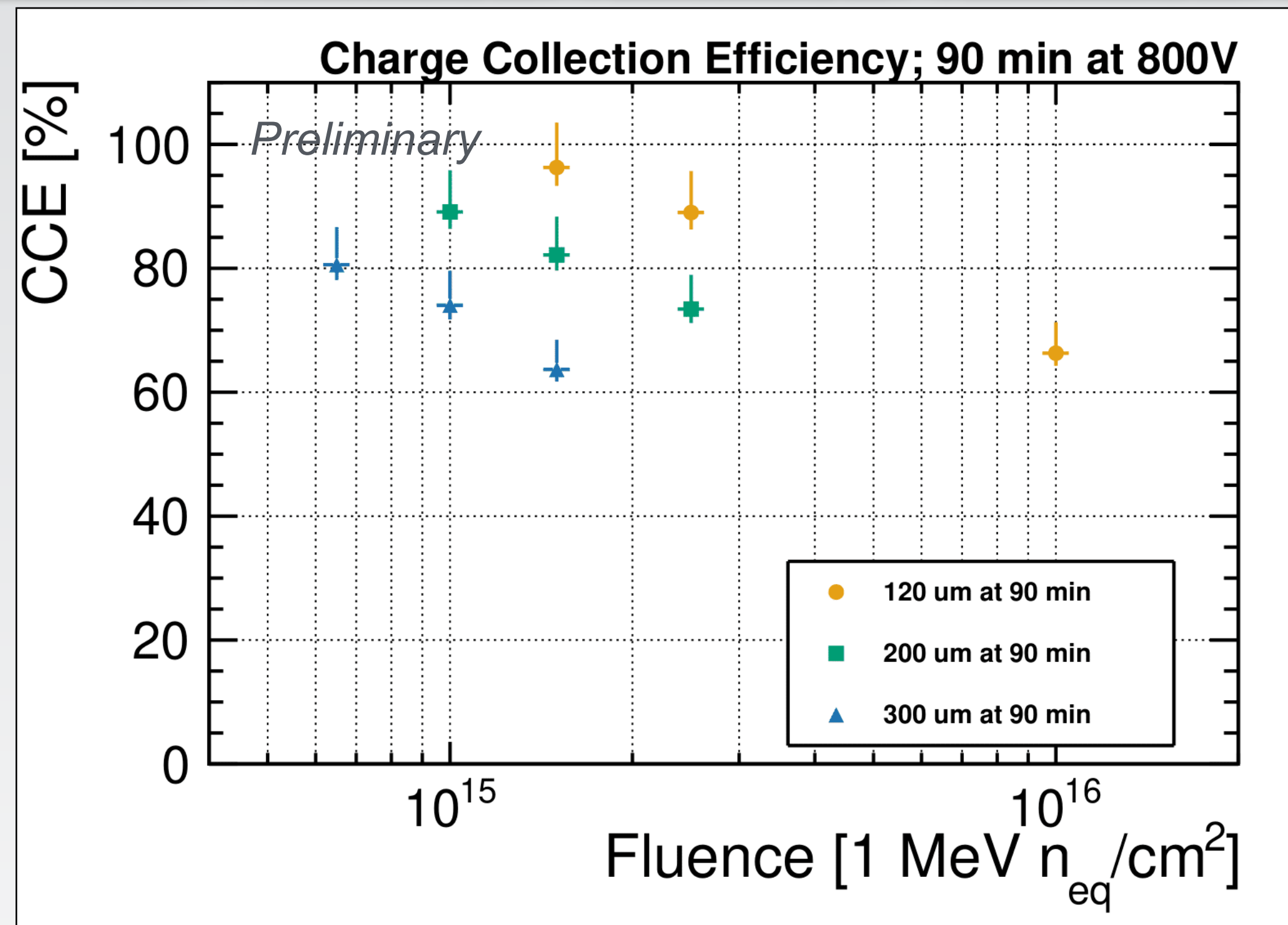
- Results being used in simulation studies to for establishing an operation/annealing scenario for HGCal

Thanks to the CERN SSD group for their support



Backup

CCE Results at 800V



- Charge collection efficiency decreases with fluence
- Charge collection efficiency 60% or higher at 600V for all fluences (approx +10% at 800V)
- No significant dependence on annealing time